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FUNDAMENTAL INVESTIGATION OF ULTRAVIOLET
RADIATION EFFECTS IN POLYMERIC FILM-
FORMING MATERIALS

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FOREWORD

This report No. IITRI-C6295-10, was prepared by IIT Research Institute for NASA-Langley Research Center under Contract No. NAS1-12549, IITRI Report No. C6295. This report, entitled "Fundamental Investigation of Ultraviolet Radiation Effects in Polymeric Film-Forming Materials", covers the period July 13, 1973 through April 12, 1974.


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Respectfully submitted,
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ABSTRACT

A literature search from 1958 to present has been conducted on the effect of ultraviolet radiation on polymeric materials, with particular emphasis on vacuum photolysis, mechanisms of degradation and energy transfer phenomena. The literature from 1958 to 1968 was searched manually, while the literature from 1968 to present was searched by using a computerized keyword system. Selected references are reviewed and discussed in this report. The primary objective of this study was to provide the necessary background information for the design of new or modified materials with improved stability to the vacuum-radiation environment of space.

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1. INTRODUCTION

Many applications can be easily identified for a material which can be prepared as a thin film and which is stable in the environment of space. One obvious application would be as a paint binder. Others include solar cell covers, second-surface mirrors, adhesives, and optical windows. Apart from ultraviolet and charged-particle radiation stability, the essential requirements of the ideal material are that it be optically transparent in the spectral region from 3000Å (preferably 2000Å) to at least 25000Å, that it be a film-former, pigmentable, and processable. For a variety of reasons, commercially available materials do not meet these requirements; most are unstable, others have high outgassing potential, and many are simply not adaptable to spacecraft applications.

The purpose of the program described in this report was to develop a comprehensive rationale for "designing" a polymeric material possessing the major characteristics noted. The basic approach is to formulate structure-property relationships: associating stability with polymeric structure or structure-related properties. The program discussed here is the first phase of this effort and essentially consists of gathering, screening and analyzing relevant information. Determining which polymeric structures are most resistant to ultraviolet and charged particle radiations, and indicating means of synthesizing new materials or modifying existing materials are this effort's ultimate objectives.

The primary information we seek is that which correlates UV-induced degradation mechanisms with structural changes which result in increased optical absorption. For this purpose, it is necessary to determine the principal factors affecting the various

modes by which a polymer dissipates absorbed UV energy, specifically, to identify those which influence the creation of optically absorbing species. The task is a difficult one because this type of information is highly specific to individual polymer structures.

2. LITERATURE RETRIEVAL

The Information Science (IS) group of IITRI Chemistry Division surveyed the availability of materials at the John Crerar Library and used the information gained there to formulate a computerized keyword search of Chemical Abstracts (CA). The library search identified about 25 summary volumes that are related to some aspects of the program. Citation cards prepared for those items that have been judged by IS to be valuable formed the nucleus of the reference abstract file. In addition, citation cards were prepared for the items that appeared in the bibliographies of those references - thus broadening the base of initial coverage. Additional broadening was achieved via the RAPRA abstracts.

When the initial library survey was completed, the most direct benefit was the accumulation of sufficient keyword frequency of occurrence data to allow formulation of a meaningful profile (search question). The first category (A) consists of terms that express the concept of "Ultraviolet Photochemistry" which is the interaction of interest. The second category (B) consists of terms that characterize the materials and other interactions of interests. Common polymer trade-names and abbreviations were also included in this category. The third category (C) specifies some interactions, other than those that are relevant, that are to be specifically excluded from the retrieval. Thus, the computer retrieval requires that each selected citation possesses at least one occurrence of an index or title term from each of the two categories, A and B, while a single occurrence from the C categories would disqualify it (Table 1).

Each citation card from the computer retrieval contains the title, author, source, index terms for the reference, as well as a special print-out of those terms that were responsible for the selection. A final card summarizes the statistics of the family of keywords, sorted alphabetically. These retrieved citations were manually prescreened by IS prior to their release to the Polymer Group for close technical review and selection of the documents to be ordered. The CA machine search (1969-1974) identified 6,582 references. The period from 1958 to 1969 was searched manually, since it does not currently exist in a machine readable form. The literature coverage was the following:

<u>Abstract Journal</u>	<u>No. of References</u>
Chemical Abstracts (CA)	
manual 1958 - 1968	12,000*
machine 1969 - 1974 (April)	6,482
Scientific & Technical Aerospace Reports	
manual 1968 - Present	50
USGRDR (GRA) 1968 - Present	40

* estimated figure - material was reviewed directly by technical staff - reference abstract cards were prepared for only most pertinent material.

Some 18,500 reference abstracts were identified and technically reviewed for the program. Approximately 500 reference documents were ordered for the program. These included government research reports, published journal articles, reprints, papers from proceedings, excerpts from handbooks, etc. The most significant works are reviewed in this report.

Table 1
Computer Retrieval Keywords

<u>A</u>	<u>B</u>	<u>C</u>
UV	Poly*	Atomic
Ultraviolet	Plastic	Alpha
Ultra-violet	Coating	Beta
Radiat	Paint	Gamma
Photo*	Resin	
	Film	
	Vacuum	
	Absorb*	
	Absorpt*	
	Degrad*	
	Silicone	
	PVC	
	Nylon	
	Teflon	
	Viton	
	Kel-F	
	Lexan	
	Kodel	
	Mylar	
	Kapton	
	Nomex	
	Neoprene	
	Saran	
	Astrel	
	Ekono1	

3. PHOTOLYTIC BEHAVIOR OF POLYMERIC MATERIALS

3.1 Ultraviolet Absorption and Photochemical Effect

The chemical changes resulting from exposure of a polymer to ultraviolet are controlled by the two fundamental laws of photochemistry that apply to any other type of non-polymeric material. The first law (generally known as the Grotthuss-Draper Law) states that only radiations that are absorbed by the material can produce a chemical change. Most polymers contain chemical groups which absorb ultraviolet light. The carbonyl group ($C=O$) occurs in many polymers and may cause ultraviolet absorption up to 2500-2800Å. Aromatic compounds absorb up to 3500Å; when combined with the carbonyl group they absorb to still higher wavelength. A carbon-carbon double bond ($C=C$) alone absorbs below 2500Å; but when several double bonds are conjugated they absorb at increasingly higher wavelength eventually reaching the visible range.

The second fundamental law of photochemistry is generally known as the Stark-Einstein law, or law of the photochemical equivalent (ref. 1): each molecule taking part in a photochemical reaction absorbs one quantum of the radiation causing the reaction. Since a quantum of energy is given by the product $h\nu$, according to the Stark-Einstein law the energy absorbed by a reacting molecule is also given by $h\nu$ (the product of Planck's constant and the frequency of the light absorbed).

If moles are substituted for molecules in the Stark-Einstein law, one obtains what is known as the Bohr law. If the energy absorbed by a molecule is $h\nu$, the energy absorbed by a mole is given by $E = N h \nu = N h c / \lambda$ (where N is the Avogadro's number and c the velocity of light). Inserting the values for N, c, h , and converting ergs into kilocalories, the Bohr law is obtained (λ is expressed in Angstrom units):

$$E = (2.86 \times 10^5 / \lambda) \text{ kcal/mole}$$

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The energy E for a given wavelength is usually referred to as the einstein of radiation; this is the energy of an Avogadro's number of photons, that is, the energy absorbed by a mole of absorbing substance. This equation allows a direct comparison between bond energies in polymers and absorbed energy at any given wavelength. For example, for a $\lambda = 4000\text{\AA}$, the einstein is 71 kcal/mole; for a $\lambda = 2537\text{\AA}$ (a common wavelength in photochemical work), the einstein is 113 kcal/mole, more than enough to break a carbon-carbon bond. Typical values of bond energies are shown in Table 2.

The relationship between the photochemical effect of a radiation and the energy absorbed is usually expressed as quantum yield or quantum efficiency ϕ :

$$\phi = \frac{\text{number of broken bonds}}{\text{number of quanta absorbed}}$$

3.2 Effects of Impurities and Extraneous Materials

A ultraviolet transparent polymer must be stable ultra-violet since there can be no damage without absorpt. Unfortunately, transparency of a polymer to ultraviolet light is difficult, if not impossible, to achieve. Polyethylene and other saturated polyhydrocarbons, for example, should be inherently transparent at wavelengths higher than 2000\AA . However, these polymers degrade under ultraviolet exposure, and the reason is that, to some extent, they do exhibit ultraviolet absorption. This absorption has been ascribed to impurities or structural irregularities in the polymer chains that may act as sensitizers of ultraviolet degradation. The problem of purity is very critical in the study of the photolysis of polymers. Conclusions relating polymer structure to stability can be misleading, if degradation is promoted by an unknown structural irregularity or impurity.

Table 2
BOND ENERGY TERMS FOR GENERAL USE^a

<u>Bond</u>	<u>Bond Energy Term E (K cal./mole, 25°)</u>
C-C	82.6
C=C	145.8
C≡C	199.6
C-N	72.8
C=N	147
C≡N	212.6
C-O	85.5
C=O aldehydes	176
C=O ketones	179
C-S	65
N-N	39
N=N	100
Si-O silicones	106? ^b

^aAll values are deduced from aliphatic compounds and are taken from T.L. Cottrell, "The Strengths of Chemical Bonds," Butterworths Scientific Publications, London, 1958, pp. 270-275.

^b? = doubtful value

that is not typical of the polymer structure. These are sites where the degradation reaction is often initiated since the energy required is lower than that required for breaking a regular bond. It is very difficult to determine the nature of the initial absorbing species, because of their very low concentration. The formation of carbonyl groups by oxidation during polymerization or processing of polyolefins may be responsible for the initial absorption and could initiate photolytic degradation (ref. 1a, 2). It has been reported (ref. 3) that aromatic impurities such as phenanthrene, anthracene and naphthalene are present in polyethylene and act as sensitizers of ultraviolet degradation. The use of model compounds in the study of polymer photolysis has the very important advantage that the study is conducted on pure materials.

3.3 Relationship Between Absorption and Stability

Although ultraviolet instability is undoubtedly related to ultraviolet absorption, the relationship between transparency and stability is not simple to predict. For example, traces of keto groups in polyethylene make the polymer very sensitive to ultraviolet light, whereas poly(methylmethacrylate) with one keto group for each repeating unit is among the polymers with the highest ultraviolet stability. It appears that some polymer structures, unlike others, have a mechanism for dissipating absorbed energy that otherwise would cause breakdown of the chain. Absorbed energy can be dissipated as heat or re-radiated at

longer wavelength. A better understanding of these phenomena would probably explain why the same absorbing group may have a negative effect on ultraviolet stability in a certain polymer structure and be relatively harmless in another structure.

An interesting question is whether the effect of ultraviolet on polymers can be predicted on the basis of a knowledge of the effect of gamma or other ionizing radiation. A few studies have been concerned with comparing the effect of ultraviolet and gamma radiation on polymers. Charlesby has demonstrated for poly(methylmethacrylate) (ref. 4) that the degradation process due to ionizing and ultraviolet irradiation is the same; only the efficiency of the two processes differ, since the energy absorbed per main chain cleavage is about 550 eV with ultraviolet radiation and about 65 eV with gamma radiation. Apart from this difference in efficiency, Charlesby concludes that the two reactions are very similar and result in the formation of similar free radicals, as seen by EPR. (It must be noted that "ionizing" radiations do not normally produce ionization in organic polymers, and the observed effects are generally explained in terms of free radical reactions with no participation of ionic species). In a following paper, however, Charlesby (ref. 5) points out an important difference between gamma and ultraviolet irradiation of poly(methylmethacrylate): the susceptibility of an ester group in polymethylmethacrylate to undergo homolysis by ultraviolet radiation is about 40 times that with gamma radiation, when compared to the susceptibility of the main chain. This pronounced difference is ascribed to the fact that while gamma radiation is absorbed at random by the polymer chain, absorption of ultraviolet is selective at the keto group of the ester link. It may be concluded that the selective absorption of ultraviolet light is responsible for the different effect of ultraviolet and gamma

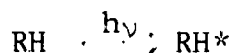
radiation. This consideration is certainly applicable to polymer structures other than poly(methylmethacrylate).

It is interesting to note that some high-temperature aromatic polymers that are highly stable to gamma-radiation, such as the polyarylsulfones, are very unstable to ultraviolet radiation (ref. 6,7,8). This behavior is often observed with aromatic structures exhibiting high absorption in the ultraviolet region.

A few studies have appeared on the wavelength dependence of photodegradation in organic polymers. As a general rule, the lower the wavelength of the radiation absorbed the greater is the damage (ref. 9). However, it has been found that, in the case of aromatic polyamides, the most damaging radiation lies in the near ultraviolet region (ref. 10). The reason for this unusual behavior is not explained. It is difficult to see how a less energetic ultraviolet radiation could cause more damage than a shorter, more energetic radiation that is equally absorbed by the polymer.

3.4 Physicochemical Aspects of Polymer Photolysis

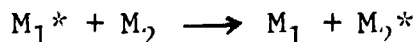
It is important to consider the various events that may follow absorption of a photon by a certain group in a polymer molecule. Most organic molecules lie in a singlet ground state. Absorption of a photon raises the molecule to an excited singlet or triplet state. If the molecule has sufficient energy in the excited state, whether it be singlet or triplet, bond dissociation may take place. This bond-breaking process is relatively slow and is statistically more probable in the long-lived triplet state. If a C-H bond is broken, the process of excitation and decomposition can be represented as follows:



This decomposition process must compete with other deexcitation processes. The excited molecule may revert to the ground state by radiationless transitions and the emission of heat. Reversion to the ground state may also be accomplished by photon emission; the excited molecule re-radiates part of the energy at a longer wavelength as the electron returns to the ground state. This phenomenon is known as fluorescence or phosphorescence, depending on whether the excited state is a singlet or a triplet, and whether or not there is a time lag in the re-radiation process. These harmless deexcitation processes allow the excited molecule to return to the ground state without producing a chemical change:

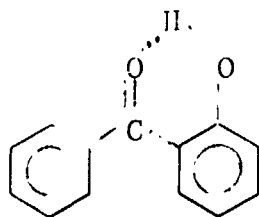


Reversion to the ground state may also be accomplished by transfer of electronic energy to another group in the vicinity of the excited molecule:



Such electronic energy transfer is believed to play an important role in polymer photodegradation, particularly where long-lived triplet states are involved (ref. 11). The importance of energy transfer processes becomes apparent if one considers that photolytic degradation is not entirely a consequence of absorption of a photon by the particular group undergoing degradation. Very often energy is transferred to this "weak" group from a different absorbing group in the polymer or from an absorbing impurity. Some workers have devoted considerable attention to the study of polymer photolysis in the presence of "sensitizing" impurities, such as the photolysis of silicones in the presence of naphthalene (ref. 12) or the photolysis of polypropylene in

the presence of phenanthrene (ref. 13). Electronic energy transfer is involved in the sensitized degradation process. An interesting case of intramolecular energy transfer is the photolysis of polymethylphenylsiloxane (ref. 14), in which photodegradation occurs predominantly at the methyl group, although the phenyl group is responsible for absorption. It is interesting at this point to observe the similarity between a "stabilizer" and a "sensitizer" of ultraviolet degradation. Both molecules are strong ultraviolet absorbers and will reach an excited state as a result of photon absorption. The "sensitizer" will return to the ground state by transfer of energy to the polymer, therefore initiating degradation. The stabilizer will return to the ground state by re-radiating the absorbed energy as heat or as a photon of longer wavelength. For a stabilizer to be effective it is essential that the energy of excitation be dissipated quickly. Since transfer of energy to the polymer is a competitive process, the rate of deexcitation is very critical. It is interesting to observe that while benzophenone is a sensitizer of photochemical reactions and is quite reactive in its excited state, o-hydroxy benzophenone is very stable to ultraviolet, and is in fact used as ultraviolet stabilizer. There is substantial evidence that the reason for the stability of o-hydroxybenzophenone is the ability of the photoexcited molecule to return to the ground state through a radiationless transition so that the energy is given up in the form of harmless heat (ref. 19,20). This behavior is undoubtedly associated with the capability of the o-hydroxybenzophenone to form an intramolecular six-membered hydrogen-bonded ring:



The excited state induced by absorption of a quantum of light is deactivated through a reversible mechanism that leaves the stabilizer molecule unchanged and does not cause any chemical effect in the polymer.

Recently it has been demonstrated that compounds that do not absorb the incident radiation can also stabilize the polymer by abstraction of the excited state energy from the polymer molecule. Guillet refers to these types of compounds as "quenchers" (ref. 15). Heskins and Guillet (ref. 16) have shown that 1,3-cyclo-octadiene can quench the excited triplet state in polyvinylketones and ethylene-carbon monoxide copolymers and stabilize these polymers against photodegradation. There is strong evidence that the mechanism of action of nickel chelates of thiobisphenols (ref. 17), that are known to be good stabilizers for polyolefins, involves primarily an energy transfer mechanism. The stabilizing effect of pyrene and p-terphenyl in poly(methylmethacrylate) was also interpreted in terms of an energy transfer mechanism (ref. 18).

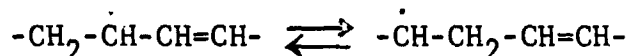
4. PHOTODEGRADATION OF VARIOUS POLYMER CLASSES

In this section, some important classes of polymeric materials are reviewed with a brief discussion of their photolytic behavior. It should be noted that because of proprietary interests, much of the literature pertaining to polymer photochemistry does not appear in scientific journals. Much of the data on photostabilization, for instance, is to be found in the patent literature. The publications reviewed here are the ones which have the greatest scientific merit and the ones that deal more specifically with the mechanisms of photolysis. Particular consideration has been given to studies dealing with photolysis in vacuum, although some studies performed in air have been included, depending upon their technical relevance, and whether or not any study performed in vacuum was available on that particular polymer.

4.1 Polyethylene

A pure polyethylene chain should not absorb radiations of wavelength higher than 2000Å. In reality, polyethylene does absorb in the ultraviolet due to impurities or irregularities in the polymer chain. Since impurities and irregularities may vary with the sample and the source of the polymer, the interpretation of the results and the comparison of data of different authors is particularly difficult. The formation of carbonyl groups as a result of oxidation during polymerization or processing is often blamed for ultraviolet absorption and consequent instability of polyethylene. Charlesby and Partridge (ref. 1a,2) have shown that carbonyl groups are indeed present in polyethylene and that the ultraviolet and gamma induced thermoluminescence and phosphorescence of polyethylene are associated with the presence of carbonyl impurities.

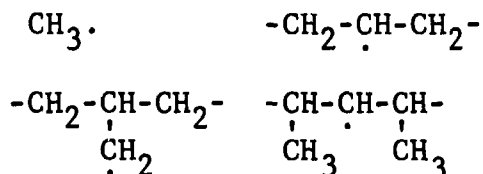
Polyethylene undergoes much faster physical change upon irradiation in air than in nitrogen (ref. 21). Charlesby (ref. 22) exposed polyethylene to 2537Å radiation both in oxygen and in nitrogen; he found that ultraviolet exposure results in an increased absorbance in the 2000-2800Å region, and ascribed the absorption to conjugated unsaturation. Cotten (ref. 23) showed that both chain-scission and cross-linking take place on irradiation of polyethylene in air, and that scission is favored in the highly crystalline region. Since the diffusion rate of oxygen into amorphous regions is greater than in crystalline regions, cross-linking occurs preferentially in the amorphous regions (ref. 24). Ohnishi (ref. 25) irradiated polyethylene in vacuum with electrons at -78°C and by EPR, found allyl radicals, these allyl radicals are converted to alkyl radicals under 2537Å irradiation. The total radical concentration does not change, indicating the existence of an alkyl-allyl equilibrium:



Pivovarov (ref. 3) reported that polyethylene always contains phenanthrene, anthracene and naphthalene as impurities, and that these aromatic compounds act as sensitizers of ultraviolet degradation.

4.2 Polypropylene

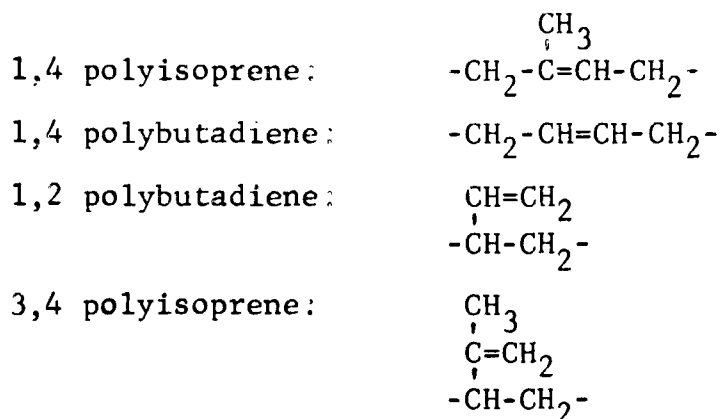
Several free radical species have been detected by Yoshida (ref. 26) and Browning (ref. 27) in the EPR spectrum of irradiated polypropylene:



Milinchuk (ref. 28) has observed the same type of allyl-alkyl free radical equilibrium described for polyethylene in the ultraviolet irradiation of polypropylene in the absence of air. In the presence of air, peroxy radicals derived from both the allyl and alkyl radical are formed. Klinshport (ref. 29) finds that the transformation is reversible and in the dark the alkyl radical is transformed into allyl radical. Malinskaya (ref. 13) has studied the photolysis of polypropylene containing phenanthrene as sensitizer. He found by EPR the same radicals described by Yoshida and Browning; he suggests that the samples studied by these workers contained undetected amounts of aromatic impurities. McTigue (ref. 30) reported that pigments are beneficial for ultraviolet stability of polypropylene and that carbon black is the most effective.

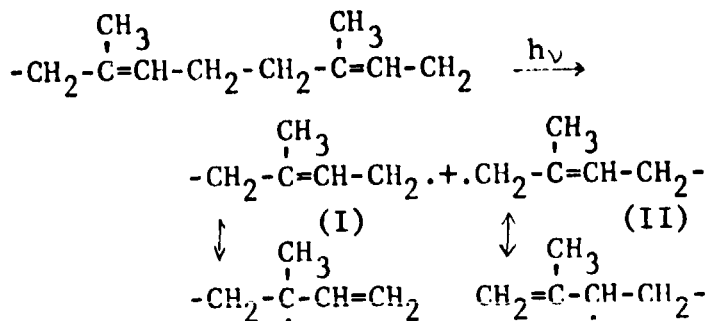
4.3 Unsaturated Polyhydrocarbons

A paper by Golub (ref. 31) reviews the photolysis in vacuum of the following unsaturated polymers:



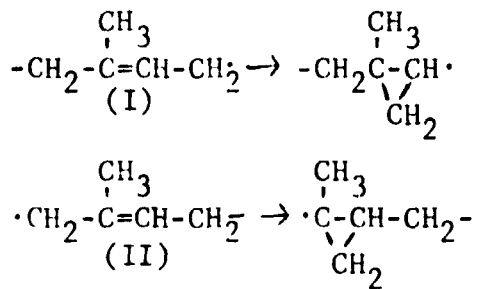
These polymers were found to undergo a radiation induced cis-trans isomerization.

In the irradiation of 1,4 polyisoprene and 1,4 polybutadiene, the energy absorbed by the double bond is diverted into breaking C-C bonds connecting the repeating units:

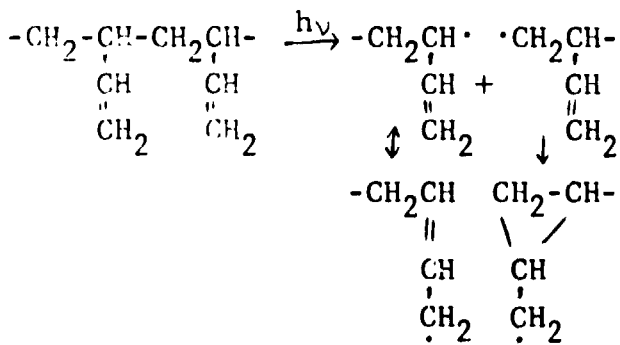


The C-C bond connecting the repeating units is the weakest bond in the chain, with a strength (55 kcal/mole) which is lowered from the normal C-C bond strength by the resonance energy of the two allyl radicals formed on chain scission.

The formation of cyclopropyl groups during photolysis is explained as follows:



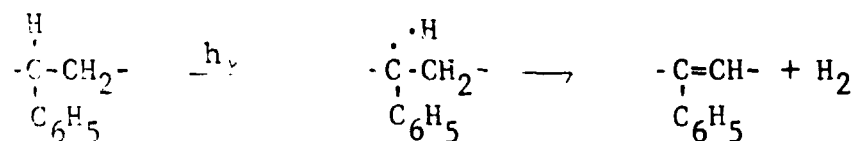
With 1,2-polybutadiene and 3,4-polyisoprene a similar process of chain cleavage takes place:



Cyclopropyl group formation takes place by a process similar to the one shown for 1,4-polyisoprene.

4.4 Polystyrene

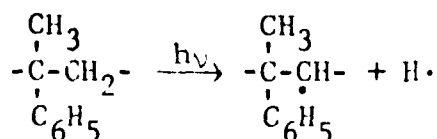
In spite of the large amount of literature on the photolysis of polystyrene, only two studies, one by Fox (ref. 32) the other by Grassie (ref. 33), deal with the mechanisms of photolysis in vacuum. These workers exposed films of polystyrene to 2537Å radiation in vacuum. They found that ultraviolet radiation causes almost exclusively cross-linking. Chain scission was negligible, unless oxygen was present. Yellowing was very pronounced, even in the absence of oxygen. Grassie suggests that color is due to conjugated unsaturation, and he points out that on melting a degraded film that was yellow the color of the melt turns immediately black. He indicates that the photolytic process that is energetically more favorable involves removal of the hydrogen atom from the tertiary carbon:



Cross-linking results from recombination of the tertiary radicals formed by hydrogen abstraction. As a general rule, the more reactive the removed hydrogen, the less reactive the resulting free radical; therefore, cross-linking occurs. Alternately, the less reactive the hydrogen, the more reactive the new free radical, and chain scission becomes the predominant reaction.

4.5 Poly(α -methylstyrene)

Substitution of a methyl group for the α -hydrogen in polystyrene results in a structure that degrades in a totally different way. In polystyrene, the photolysis involves exclusively cross-linking, whereas in poly(α -methylstyrene) photolysis involves exclusively chain scission:



The reason for the different behavior is due to the fact that a relatively stable tertiary radical is formed with polystyrene while an unstable secondary radical is the precursor to the more rapid chain scission occurring in poly(α -methylstyrene). The less stable the radicals, the more likely are they to decompose rather than to combine to give cross-links (ref. 34).

Stokes and Fox (ref. 35) have studied the photolysis of poly(α -methylstyrene) films in vacuum. Monomer is formed by depolymerization and the monomer yield increases with increasing temperature. At 27°C, the quantum yield for random scission was 10^{-3} and for monomer formation 7×10^{-3} (approximately 7 monomer units for each scission). At 155°C, the quantum yield for scission was 2×10^{-2} and for monomer formation 0.5 (approximately 25 monomer units for each scission).

4.6 Fluorocarbon Polymers

Many papers have been published on the effects of gamma irradiation on fluorocarbon polymers, but very little has been published on ultraviolet irradiation. Bowers (ref. 36) studied the cross-linking of fluoropolymers by irradiation at elevated temperatures. The source used was a Pen-Ray quartz mercury lamp, emitting radiation principally at 1849 and 2536Å. Under nitrogen, ultraviolet irradiation of poly(chlorotrifluoroethylene) at 250°C resulted in degradation while only minor degradation was observed with poly(tetrafluoroethylene) at 325°C; no cross-linking was noted. With Teflon 100 FEP (a copolymer of tetrafluoroethylene and hexafluoropropene) both scission and cross-linking occur and the latter increases with increasing temperature.

Stephenson (ref. 37) studied the photolysis of polytetrafluoroethylene both in nitrogen and vacuum. Unlike other polymers, the drop in tensile strength and elongation by irradiation

with 2537⁰Å ultraviolet light is more rapid in vacuum than in nitrogen. A study of the wavelength dependence of photodegradation of poly(tetrafluoroethylene) showed that the efficiency in producing degradation increases with decreasing wavelength (ref. 37). A study of the absorption spectrum of polytetrafluoroethylene (as well as of other unfluorinated polyhydrocarbons with no natural absorption in the ultraviolet) showed that polymer absorption and luminescence in the UV range are due to aromatic impurities (ref. 3).

4.7 Poly(methylmethacrylate)

The photolysis of poly(methylmethacrylate) has been studied in great depth by several workers. The photolytic process is very similar to poly(α -methylstyrene), in that the polymer undergoes random chain cleavage with no cross-linking. Photodegradation at room temperature produces small amounts of volatile materials, but the formation of monomer by "unzipping" increases with increasing temperature.

Fox (ref. 9) points out that because of the low absorption coefficient of poly(methylmethacrylate) at 2537⁰Å, this radiation can penetrate a thin film with only slight attenuation, whereas with more highly absorbing polymers a "skin" effect is produced. The photolysis of poly(methylmethacrylate) was studied in vacuum at 25°C with a medium pressure mercury lamp. The quantum yield for random scission is 4×10^{-2} . Methyl formate, methanol and methylacrylate are formed in quantum yields of 0.14, 0.48 and 0.20, respectively, indicating a depolymerization of about five monomer units for chain break (ref. 38).

Charlesby and Thomas (ref. 4) studied the photolysis in vacuum, air and nitrogen. Surprisingly, the quantum yields in air or nitrogen are lower than in vacuum. Fox (ref. 9) points out that oxygen might act as an inhibitor by scavenging secondary polymer radicals which are precursors to chain scission. While nitrogen might suppress the diffusion of gases from the film, it is difficult to see how this could affect the rate of scission.

Many workers have noted the appearance of a new band at 2850Å in ultraviolet irradiated poly(methylmethacrylate). This new band appears by irradiation either in air or vacuum, and remains with the polymer even after reprecipitation, indicating that the absorbing group is part of the chain (ref. 38). Fox (ref. 38) ascribes the 2850Å absorption to a carbonyl chromophore formed by secondary reactions after homolysis of the ester. Frolova (ref. 39) ascribes it to conjugated unsaturation in the chain, because the absorption shifts to higher wavelengths during irradiation. He supports this conclusion with a study of the IR spectrum of the irradiated polymer that shows new bands at 1615 and 1640cm⁻¹ indicative of the presence of olefinic unsaturation.

Electron spin resonance spectra of ultraviolet and gamma irradiated poly(methylmethacrylate) are identical, indicating that the same free radicals are present in the irradiated polymers (ref. 40,4).

4.8 Poly(methylacrylate)

A study by Fox (ref. 41) indicates the formation of a weak band at 2800Å on irradiation in vacuum at 2537Å. The main volatile products are formaldehyde, methanol and methylformate (from ester group decomposition), along with CO₂ and hydrogen. The rate of CO₂ formation increases with dose; since the enu-group concentration increases with dose, it is suggested that CO₂ comes from the terminal end groups.

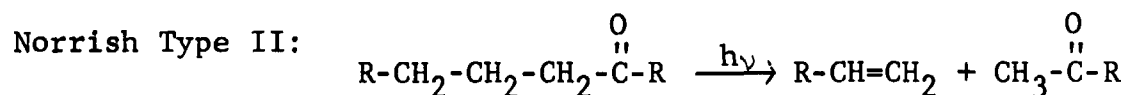
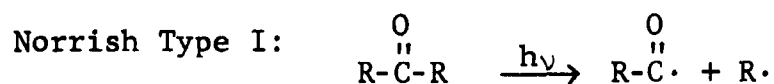
4.9 Poly(ethylacrylate)

A study by Jacobs (ref. 42,43) shows that both cross-linking and chain scission take place during irradiation. The time necessary to produce insoluble gels increases with decreasing temperature. Below the glass transition temperature (-17°C) there

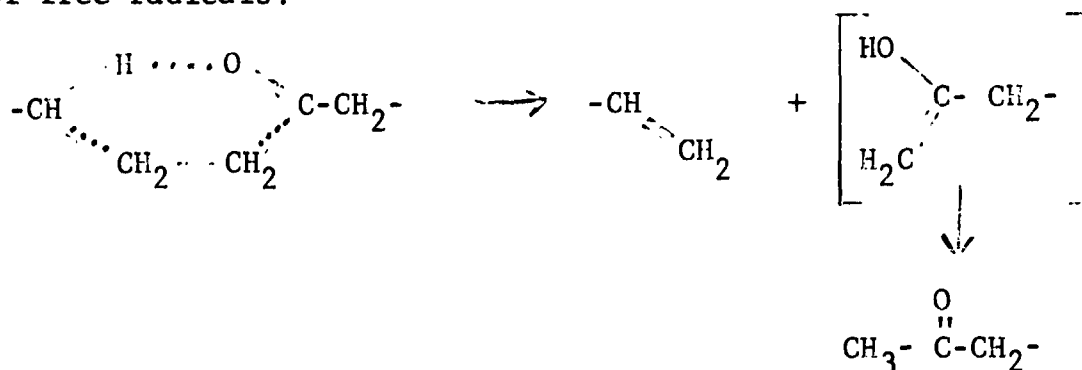
is no formation of insoluble products. It appears that when the mobility of the chain is reduced, the recombination of radicals to give cross-links is less likely to occur.

4.10 Polyketones

The study of the photolysis of polyketones is particularly interesting because the photolysis of simple aliphatic ketones is a well understood process. Two primary reactions are known to occur in the photolysis of aliphatic ketones:

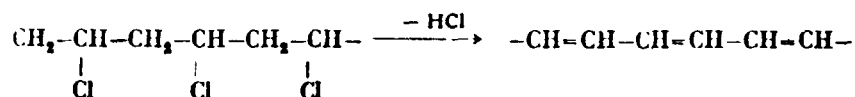


Wissbrun (ref. 44) studied the photolysis of poly(methylvinylketone) at 3130Å. An increased absorption below 2500Å was observed, and acetaldehyde, carbon monoxide and methane were formed in quantum yields of 0.06, 0.003, and 0.0006 at 80°C. Guillet (ref. 45) studied the photolysis of poly(methylvinylketone) and polyethylene-carbon monoxide copolymer. He finds that the photolysis of polyketones is described very well by the Norrish type I and II. It is interesting to note that the Norrish type II follows a molecular mechanism that does not involve formation of free radicals:



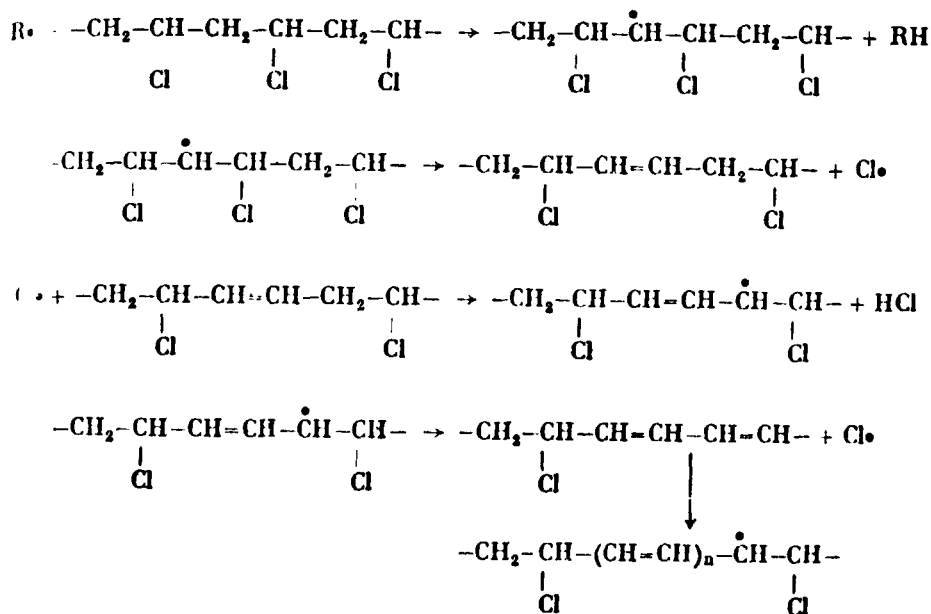
4.11 Polyvinylchloride

The spectroscopic changes produced by ultraviolet irradiation in vacuum of PVC films have been studied by Golub (ref. 96). The main photoolytic effect is the formation of a conjugated polyene system through progressive loss of HCl:



As the sequence of conjugated double bonds increases, absorption increases progressively from the ultraviolet to the visible portion of the spectrum. Consequently, PVC films become increasingly colored on irradiation. The quantum yield for HCl formation is independent of wavelength below 3400Å, which is the effective photochemical cut-off wavelength.

The following free-radical mechanism has been proposed for the dehydrochlorination reaction:

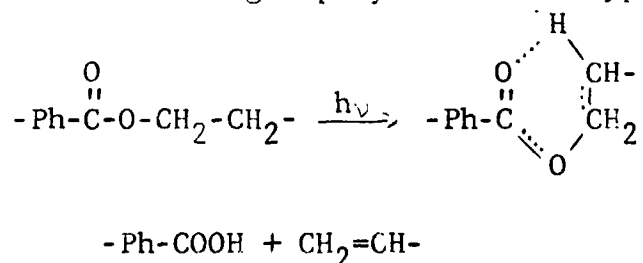


4.12 Polyacrylonitrile

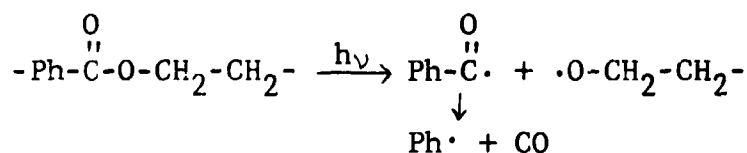
Jellinek (ref. 46) reported that exposure of polyacrylonitrile to 2537Å irradiation in vacuum results in cross-linking and formation of HCN. Fox (ref. 9) points out that the longest wavelength absorption maximum of the nitrile group is about 1600Å. Polyacrylonitrile should therefore, be very transparent to ultraviolet. However, absorption occurs with a maximum at 2650Å that is somehow associated with the polymer structure itself. The chromophore causing the absorption has not been identified.

4.13 Polyesters

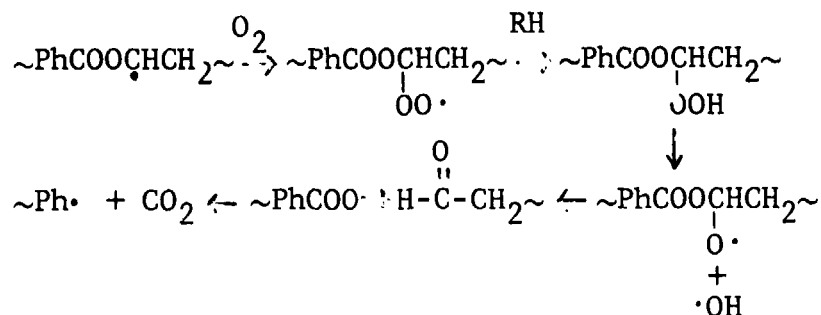
Three recent papers have been published by Day and Wiles on the photolysis of poly(ethyleneterephthalate) in nitrogen and air (ref. 47, 48, 49). As a result of irradiation, an increase in carboxyl groups was observed, that was ascribed to the decomposition of the ester group by a Norrish Type II process:



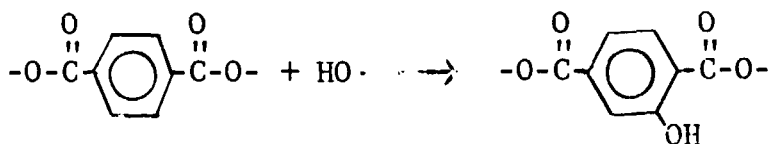
They found that CO and CO₂ were the major volatile products and that CO₂ was formed primarily in the presence of air. The formation of CO was explained on the basis of a Norrish Type I cleavage reaction:



The fact that CO_2 formation takes place primarily in the presence of oxygen suggests that hydroperoxidation is involved:

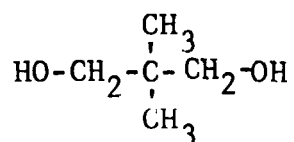


Another phenomenon observed in poly(ethyleneterephthalate) irradiated in the presence of air is the appearance of a fluorescent band at 4600Å. This band was ascribed to the formation of an hydroxylated derivative resulting from the attack of the OH radical (formed from the reaction above) on the phenyl ring:

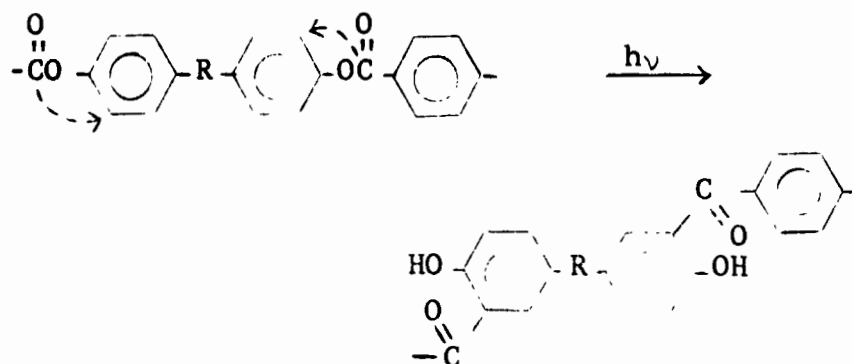


The nature of the fluorescent product was confirmed by Pacifici (ref. 50) who compared the fluorescence spectrum of irradiated poly(ethyleneterephthalate) with that of synthetic hydroxylated polyesters.

It has been reported (ref. 51) that polyester compositions based on neopentylglycol exhibit superior ultraviolet resistance. This is probably due to the fact that the cleavage of the ester via Norrish Type II cannot occur because of the absence of hydrogen on the carbon atom β to the hydroxyl groups in neopentylglycol:

$$\begin{array}{c} \text{CH}_3 \\ | \\ \text{CH}_2 - \text{C} - \text{CH}_2 - \text{OH} \\ | \\ \text{CH}_3 \end{array}$$


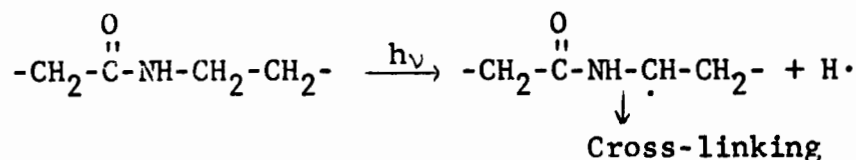
A paper by Cohen (ref. 42) describes a number of aromatic polyesters that under ultraviolet irradiation rearrange to an o-hydroxybenzophenone structure according to the photo-Fries reaction:



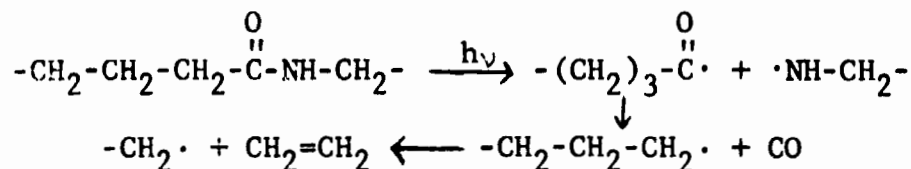
These polyesters are reported to be useful as coatings for protecting substrates ordinarily sensitive to ultraviolet light. We did not find any work dealing with the ultraviolet irradiation of polycarbonates.

4.14 Polyamides

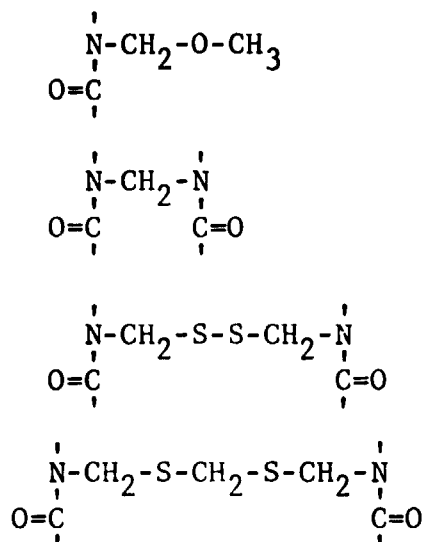
A paper by Moore (ref. 53) deals with the photolysis of Nylon 66 and of model N-alkyl amides both in nitrogen and air. Both crosslinking and chain scission were found to occur. The mechanisms proposed are basically in agreement with the mechanisms proposed previously by Rafikov (ref. 54). The mechanism for cross-linking involves elimination of a hydrogen atom from the carbon adjacent to the nitrogen atom followed by combination of two radicals:



The mechanism for chain scission involves cleavage of C-N bonds with subsequent formation of CO and ethylene:

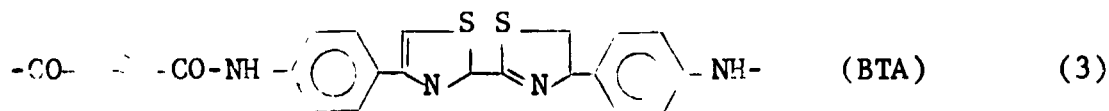
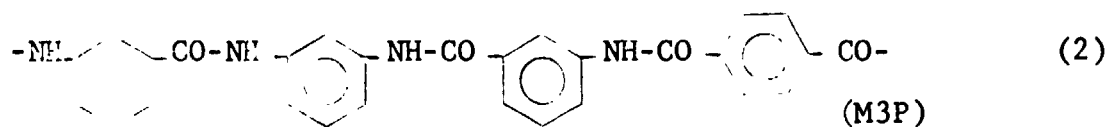
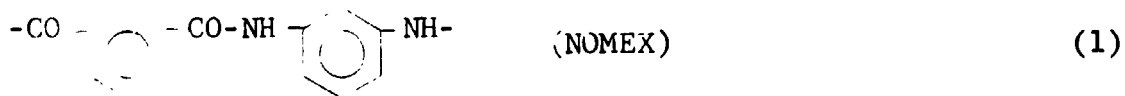


Brick (ref. 55,56) reported some structural modifications of Nylon 6 that produce a fiber crimping effect. The following Nylon 6 modifications were considered:



These structures were reported to possess good ultraviolet stability (with the exception of the disulfide). Comparative data with the ultraviolet stability of unmodified Nylon 6 were not given.

A paper by Johnson (ref. 10) discusses the photodegradation of three aromatic polyamides:

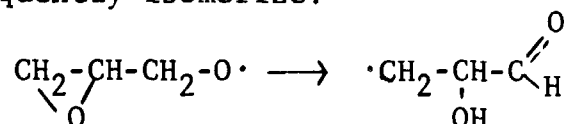


A study of the wavelength dependence of photodegradation shows that all three polymers are degraded by light of much longer wavelength than that which is harmful to other polymers. Polymer (1) and (2) show degradation maxima at 3600 and 3700Å; polymer(3) is degraded significantly even by visible light (particularly 4140Å). The mechanism of degradation is not known.

A study by Krasny (ref. 57) on the photostabilization of Nomex fibers confirms that Nomex is particularly sensitive to photodegradation in the wavelength region of 3600-3900Å. Ultra-violet stabilizers exhibiting strong absorption in this critical wavelength region were found to be unsatisfactory because of polymer incompatibility or other undesirable effects.

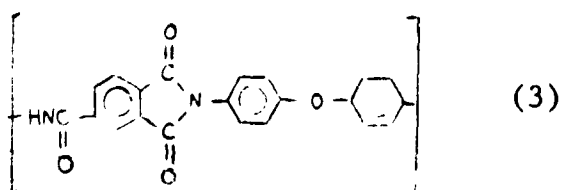
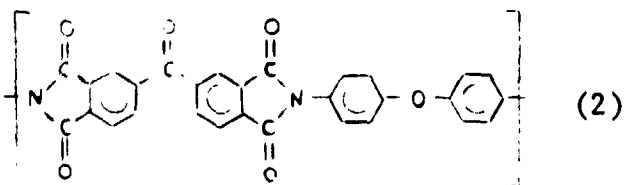
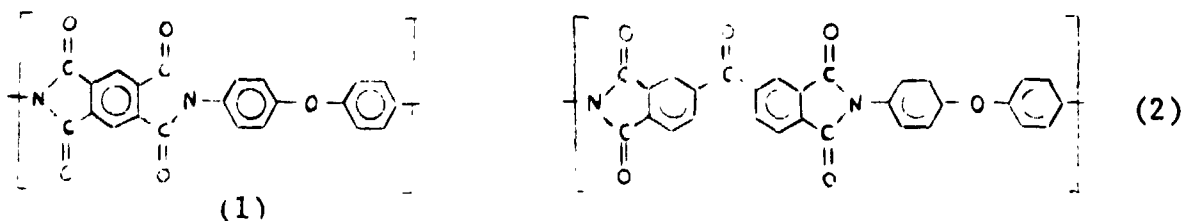
4.15 Polyethers

Kelleher (ref. 58) studied the photooxidation of poly(oximethylene) and found that random chain scission occurs followed by extensive depolymerization to formaldehyde. A similar process occurred in a oxyethylene-oxymethylene copolymer, except that depolymerization appeared to stop at the ethylene unit. Grassie (ref. 59) studied the photooxidation of poly(oxymethylene) at 2537 and 3650Å. Hydrogen and carbon monoxide were the main decomposition products. Irradiation in air produced well defined changes in the hydroxyl and carbonyl regions of the infrared spectrum. Irradiation at 2537Å was approximately 100 times more effective than 3650Å irradiation. Sukhareva (ref. 60) studied the spectra of ultraviolet irradiated epoxy coatings and observed the appearance of a band with a frequency of 1685cm^{-1} that was ascribed to the carbonyl group. Carbonyl group formation takes place by a radical mechanism of epoxy decomposition at the terminal groups, leading to the formation of free radicals that can subsequently isomerize:



4.16 Polyimides and Polyamide-imides

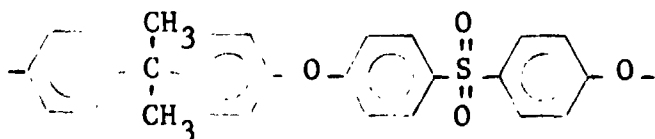
Alvino (ref. 61) studied the ultraviolet stability of the following polyimides and polyamide-imide:



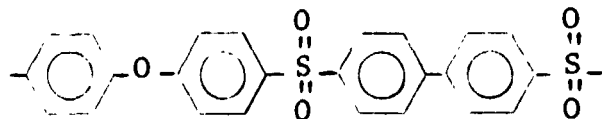
He found that these polymers were sensitive to ultraviolet light, especially in the presence of moisture. The mechanical and electrical properties of (3) deteriorated more rapidly than those of (1) and (2) under both wet and dry conditions. The increase in deterioration rate on going from dry to wet environment was much greater for (1) and (2) than for (3), indicating that (3) had greater hydrolytic resistance. The electrical properties of (1) and (2) were unaffected by $\leq 6000\text{hr}$ irradiation in a dry environment.

4.17 Polysulfones

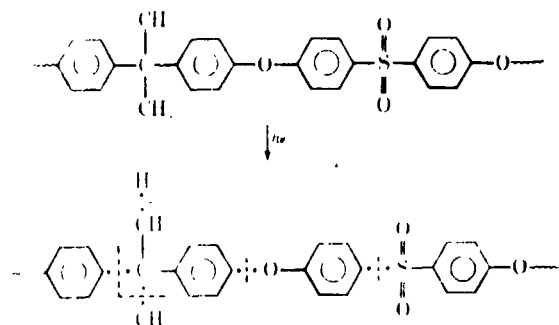
Aromatic polysulfones have been reported to possess outstanding resistance to high energy radiation (ref. 6). Their ultraviolet stability, however, is very poor. Poor ultraviolet stability has been reported for the Union Carbide polysulfone (ref. 7):



and for the 3M polysulfone ("Astrel" 360) (ref. 8):



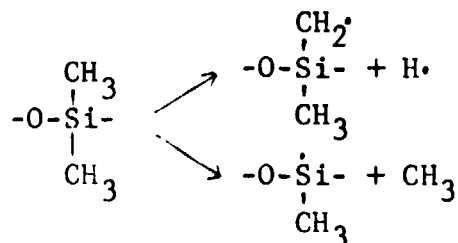
The work of Gesner and Kelleher (ref. 7) provides a good description of the photo-oxidative behavior of the Union Carbide polysulfone, which is consistent with a random chain scission mechanism. In the initiation process, scission apparently takes place at every bond except the aromatic C-C and C-H bonds:



The work of Alvino (ref. 8) on 3M polysulfone shows some interesting analogies with the results obtained by Gesner and Kelleher on the Union Carbide polysulfone. Both works indicate the formation of short chain molecules with acid functionalities (sulfonic acid groups) resulting from chain scission reactions.

4.18 Silicones

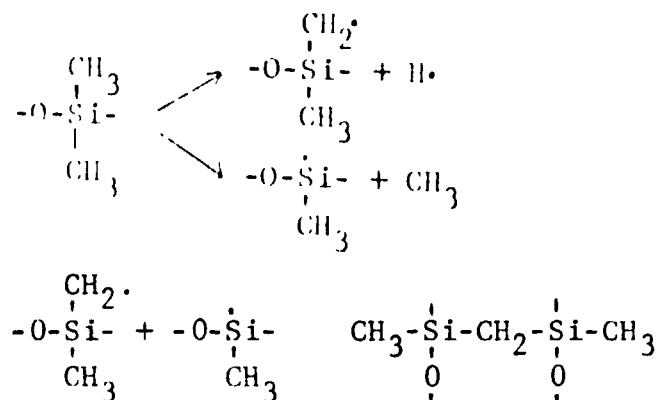
Siegel and Judeikis (ref. 12) studied the photolysis of poly(dimethylsiloxane) samples containing naphthalene as sensitizer. The samples were irradiated in the cavity of an ESR spectrometer. A mercury arc lamp having essentially zero output below 2400Å was employed. The process by which the polymer molecules become excited involves a transfer of electronic energy from naphthalene in an excited triplet level. Decomposition occurs via Si-C and C-H bond rupture. In the initial stage of photolysis, the following reactions take place with essentially equal probability:



All the resulting radicals were identified by means of their ESR spectra, with the exception of the hydrogen atoms that presumably react immediately to form H_2 and $-\text{CH}_2\cdot$ radicals.

Zhuzhgov (ref. 14) studied the photolysis of poly(methylphenylsiloxane) in the cavity of an ESR spectrometer. No sensitizer was added, but absorption was promoted by the presence of the phenyl group in the polymer. The ESR spectrum indicated the formation of $\text{CH}_3\cdot$ and $-\text{CH}_2\cdot$ radicals. Formation of $\text{CH}_3\cdot$ radicals appears to involve a two-step process requiring the absorption of two quanta of light (biphotonic mechanism). No evidence was found in the ESR spectrum for the formation of silicon radicals, which must have formed at the same time as the methyl radicals. Volatile products were hydrogen, methane and ethane in the ratio 25:70:5. The same volatile products were also reported by Siegel for poly(dimethylsiloxane) (ref. 10).

Delman (ref. 62) studied the effect of ultraviolet irradiation in air on a methylsiloxane resin. Infrared spectroscopy was employed in this study. Formation of Si-CH₂-Si linkages was observed as a result of irradiation at wavelengths above 2810Å from a Zenon arc lamp:



On the other hand, Si-OH and Si-CH₂-CH₂-Si linkages were formed when the resin was exposed to the shorter wavelength of a mercury vapor lamp. The different effects on the resin induced by the two ultraviolet sources are attributed to the fact that the mercury vapor lamp radiation is sufficiently energetic to cause the excitation of oxygen molecules. The excited oxygen molecules prevented the formation of Si-CH₂-Si linkages by interacting with the Si· radicals (formed by cleavage of Si-C bonds) to produce Si-OH.

Siegel and Stewart (ref. 63) studied the photolysis of poly (dimethylsiloxane) in the vacuum-ultraviolet region (this region starts at 2000Å and extends to shorter wavelengths where it merges with the X-ray region). The wavelengths employed were 1470 and 1236Å. Analysis of the data indicated that the breaking of the Si-CH₃ bond is the most probable reaction occurring at both wavelengths. A comparison with the photolysis of a mixed methyl-

phenyl silicone polymer demonstrated the strong protective effect produced by aromatic substituents in this region of the ultra-violet spectrum. This was determined from quantum yield measurements for the formation of volatile products.

A similar stabilizing effect of aromatic substituents is known to occur when silicones are exposed to high energy, ionizing radiation, presumably because of the ability of the aromatic ring to dissipate some of the absorbed energy before bond rupture occurs (ref. 64).

5. CONCLUSIONS AND RECOMMENDATIONS

The design of a polymer structure that is stable to the ultraviolet environment of space must take into consideration the fundamental fact that most polymers absorb the short wavelength, unfiltered ultraviolet radiation below 3000Å, that exists above the upper atmosphere of earth. Furthermore, the quantum yield for photochemical reactions is higher for the short wavelength ultraviolet, that is, the damage per quantum absorbed increases with decreasing wavelength.

The design of a polymer structure that would be highly transparent down to 2000Å appears to be an interesting approach. In this respect, it should be interesting to investigate the photolysis of pure polymethylene, the simplest of all polyhydrocarbon structures. Nothing has been published on its photodegradation. Also, high purity aliphatic and fluoroaliphatic polyethers should meet the requirement of transparency to the short wavelength ultraviolet. However, these polymers may be expected to be sensitive to the presence of adventitious impurities or residual catalysts that would cause absorption and initiate photodegradation. This is known to be the case, for example, of the fundamentally transparent methylsilicones, in which traces of absorbing impurities have been found to sensitize photodegradation (ref. 12).

Previous work has considered the use of various metallocene absorbers as a means of stabilizing organic coatings to the short wavelength ultraviolet of space (ref. 65, 66). Unfortunately, several problems are associated with the use of ultraviolet stabilizers, such as compatibility with the polymer, possible migration of the stabilizer additive, volatility and extractability. These problems can be overcome by having a polymer structure in which the ultraviolet stabilizer is part of the

polymer chain. An example of this approach is the synthesis of polymers or copolymers based on acrylate and methacrylate monomers containing pendant ultraviolet stabilizing groups, such as phenylsalicylate (ref. 67) or 2-hydroxy-4-alkoxybenzophenone (ref. 68). Therefore, an interesting approach that should be investigated is the development of a polymer structure capable of completely dissipating the absorbed ultraviolet energy by luminescence (fluorescence or phosphorescence) or by the emission of heat. These effects would allow de-excitation of the absorbed radiation without chemical change in the polymer structure. Since these are the mechanisms of action of ultraviolet stabilizers, the theory of ultraviolet stabilization would be directly applicable to the design of such a polymer structure.

Another interesting approach is to study how certain mechanisms of degradation that are energetically favored can be prevented by appropriate structural modifications of the polymer. An example of this approach would be a polyester structure with no hydrogen on the carbon atom in β to the oxygen link in the ester group; the lack of β -hydrogen would prevent chain cleavage by a Norrish Type II. For example, it has been reported that polyesters based on neopentylglycol exhibit superior ultraviolet resistance (ref. 51). Although the reason for this behavior was not explained, the improved stability is probably due to the lack of β -hydrogen in the ester structure based on neopentyl glycol.

Another interesting approach is the study of polymeric structures in which the photochemical reaction does not involve chain cleavage or other degradative effect, but it produces a chemical rearrangement that has no appreciable effect on the physical and optical properties of the polymer. This is the case,

for example, of the Fries rearrangement of aromatic polyesters that rearrange under ultraviolet irradiation to a stable o-hydroxybenzophenone structure (ref. 52). This approach could be extended to the study of fully aromatic polycarbonates (phenyl carbonates, like phenyl esters, are known to undergo the photo-Fries rearrangement). A study of the photolysis of a model compound such as diphenylcarbonate would provide directly applicable information.

Since photolytic reactions normally involve free radical processes, EPR spectroscopy of polymers irradiated under vacuum can be very useful for the study of radical species occurring during photodegradation. In this type of work, the use of model compounds has the advantage that the results are generally easier to interpret and yet are directly applicable to the polymer itself.

Aromatic polyamides exhibit unusual ultraviolet behavior, in that near ultraviolet radiation (3600-3700Å) is more damaging than ultraviolet of shorter wavelength (ref. 10). Since nothing is known about their mechanism of photodegradation, a study of the irradiation of model aromatic amides by EPR spectroscopy would be very useful in order to understand, and possibly prevent, this effect. Ultraviolet stabilizers that absorb in the critical 3600-3900Å region have been considered for Nomex stabilization, but have the inherent disadvantage that they also absorb visible light (ref. 57). It should be interesting to evaluate ultraviolet "quenchers" that would stabilize the polyamide by extraction of the excited state energy rather than by absorption in the near ultraviolet.

Perhaps the least understood aspect of polymer photodegradation is the progressive increase in ultraviolet absorption at longer wavelengths that gives rise to the well known "polymer yellowing". Many workers have studied the mechanisms of photolysis in terms of its effect on chain scission, cross-linking or other

chemical or physical changes, but little has been done to explain the reason for the "polymer yellowing" that always accompanies other degradative phenomena. Production of color is usually associated with the delocalization of electrons that accompanies multiple conjugated unsaturation. For example, formation of polyene (a chain of conjugated double bonds) has been indicated as the cause of yellowing in irradiated PVC (ref. 69). However, the mechanism of color formation during irradiation of most polymer structures is not known. Since optical stability is of primary importance in space coatings, consideration should be given to the study of the nature of colored by-products and to the mechanism of their formation. Since carbonyl groups occur in many polymers (such as acrylics, polyesters, polyamides, polyurethanes and even in polyolefins as structural irregularities), and since free radical decomposition reactions (Norrish Type I or equivalent) lead to the formation of R-CO· radicals, it seems to us that recombination of R-CO· radicals to form α -diketo groups may be a possible cause of color formation during polymer photolysis.

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APPENDIX

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Polyethylene 1

Material	Environ Cond	Irradiation Source	Additive	Anal. Method	Results		Ref
					Phys. and Optical Effects	Photoysis Products	
HDPE (Sholes 6000)	Vac. 10 ⁻³ mm. Hg r.t.	Co-60 beam with Toshiba HP400, HP HG lamp 10 ³ rad. λ 390nm with UV-39 filter		Japan Electron Optics Lab Corp. Type JEM-RSR Hitachi EDS-2, UV spectrometer fractionation	Lower viscosity, more than 50% rel. decrease in solubility and av. free rads. 285m, triene 275m, gelation	Allyl free radical 258m, allyl radical dienes 236m, dienyli free rads. 285m, triene 275m, gelation	70
PE Model Copolymer Vaseline	Vac.	Atomic pile BEPO, at Harwell		PE IR Spect. Iodometry		Trans vinyl vinylene vinylidene	71
Poly A,B,C,D (lower PE) Poly E (Random copolymer of ethylene and butene-1) Poly F (Block copolymer of ethylene-butene-1)	Vac	Electron radiation 100 Mrad dose		Material balance viscometry, density determination	Discoloration, change in density, etc. H ₂ O and CO ₂ (Oxid Prod)		72
PE (Merlex 5003) DPM-1 low density PE)	Air	60Co γ ray, 0.67 Mrad/hr CE 1-mv resonant generator, 100 Mrad/hr generator 65.4-A-10 325 W HP HG Lamp 184.9nm to visible	2,6-di-t-BU- methylphenyl 0.02%	Beckman DK-2 ESR, IR		Diene 275m Triene 275m Pentadiene 340m Free Radicals 275m Dienyl 285m Trienyl 335m Tetraenyl 359m Pentaenyl 396m	73
a) Merlex 5003 b) PE (isotactic) c) PE (isotactic)	Air r.t.	See above 0.66 Mrad/hr dose rate.		Beckman DK-2		Sample λ c (dienes) a) -196 0.20 b) -196 0.16 c) -196 0.071 -196 0.072	74

1) Photoirradiation w/o filter gives allyl radicals which when heated at r.t. 10hr gives the allyl rads. due to hydrogen migration. 2) Photoirradiation with UV-39 filter main chain scission occurs $\text{CH}_2\text{-CH}(\text{CH}_3)\text{-CH}_2\text{-}$ type. free rad is observed to migrate to allyl free rad on heating and further to the allyl free rad. Photoirradiation with UV-39 filter gives lower m.w. than mere γ radiation, also the viscosity average m.w. was lower.

Total unsaturation obtained from IR and iodometry is not in good agreement. The difference may be due to interaction of reagent with residual reactive center. Double bond production is not directly proportional to radiation dose, due to reagent hydrocarbon impurities. The hydrocarbon impurities oxidized with each event is 5 eV which is the magnitude of bond energies involved.

Linear PE, O₂ uptake 35 ml/g, 100°C reaction rate and O₂ uptake declined with thickness. Density 0.99523; 20ml/g uptake after 6000 after 5 ml/g O₂ decrease of viscosity on uptake of O₂. Branched PE, O₂ uptake 180 ml/g, 100°C density 0.931 to 0.96 O₂ uptake has a sharp rise approximately 30 ml/g. The rise in density is due to the formation of crosslinks. Autooxidation of PE is largely diffusion dependent and is confined to disordered regions. Crosslinks primarily interfere with chain crystallization while branches affect the post-crystallization reaction.

Resolution of the 236m absorption to diene is reaffirmed. Also of the higher polyenes, triene, tetraene and pentaene are reaffirmed. The resolutions of the higher polyenyl has been made, however, the $\Delta \lambda$ max has not been elucidated.

It was observed that unlike conjugated dienes, the trienes at 275m are more stable than the dienes. The stability of diene group. Higher polyenes stability at r.t. suggests free radical migration for its occurrence. Conversion of allyl to allyl free radical is an endothermic process. Reactions involving carbonium ion and free radicals satisfy both UV and ESR spectra. The mechanism of free radical migration is a distinct possibility. Hydrogen atom migration is a plausible mechanism for higher polyenyl.

Polyethylene 2
(Teflon Included)

Material	Environ. Cond.	Irradiation Source	Additive	Anal. Method	Phys. and Optical Effects	Photoysis Products	Ref.
WMC18 Alkathene Masticite DPO 4400 (all low density PE)	Air -175 r.t.	Co-60 γ ray, 3.0 Mead/hr	Biphenyl benzene, 1-hexene	UV Spectrometer, V. Spectrophotometer, luminescence spectra	Intrinsic, viscosity decrease	Dienes are formed as a single primary reaction. The radicals were differentiated by optical (trans and electron) and chemical (dienes) bleaching. Thermal H atom (H ₂) was studied by adding benzene which gives cyclohexadienyl radical. C (H ₂) = 1.8 and 1.0 (H ₂) = 0.35. This method of ion formation was relied on and the main radical species formed was identified. The radical species was distinguished by "deep" (or amorphous) and "shallow" (or crystalline) electron traps with degree of bleachability. Shallow trap readily destroyed by high dose radiation.	75
PE PP PTE PVC		DBSH-1000	Naphthalene phenanthrene anthracene			1.) The 200m absorption in purified PE, PP, PTE, PVC are due to presence of some derivatives of naphthalene, phenanthrene and anthracene. 2.) Addition of these impurities accelerated photodecomposition. 1.) The transition of naphthalene to the photochemical products was studied by the use of a photochemical via the triplet state of the sensitizer. 4.) Phenol, p-phenylenediamine, 1- and 2-naphthylamine and naphthol derivatives have sensitizing effects.	3
PTE (forms of rod, blocks or sheet) T. & E. a) (Fluorocarbon Co.) b) Teflon 7 (DuPont Co.)	Vac. and Air	Co-60 γ source (UCLA Labs. Atomic Intn'l., U. Cambridge Mass. Lab. and Stanford Univ. Lab. and University of California)		Verlan V-4502, X-band ESR		At 10 ⁶ to 10 ⁸ rads, the chain to propagating radical ratio is 10:1. In air peroxide radicals are formed in the same ratio. In air-saturated rod the same two radicals form with chain peroxide predominating at 10 ⁶ rads. The rate and extent of decay of peroxide radicals was studied. The decay of peroxide radicals in air-saturated PTE as a function of total dose is linear thus, PTE is useful as dosimeter. Dose-depth curve obtained from radical concentration vs thickness gave linear curve.	76

Abbreviations as follows

- HDPE: High density polyethylene
- PE: Polyethylene
- PP: Polypropylene
- PTE: Polytetrafluoroethylene
- PVC: Polyvinylchloride

Polypropylene

1

Material	Environ. Cond.	Irradiation Source	Additive	Anal. Method	Results			Ref.
					Phys. and Optical Effects	Photolysis Products	Conclusions	
PP (Isotactic) PET (Mylar) Ethyl benzoate (Model cop)	Vac.	Hg lamp, 250m Weather-meter Zenon and Carbon Arc		IR	Weight loss Increase in refractive index Discoloration.	PP hydroperoxide (3400cm ⁻¹) CO (2400cm ⁻¹) CH ₃ COOH H ₂ O PP ketone (4-0.1) 410 ⁶ PET COOH CO Vac 17.2 6 1 1.1 Air 18.3 8.7 8.7	Photooxidative changes are confined to the surface. Photooxidation products from thermal oxidation or from irradiation in air. Photooxidation of PP in air and CO and O ₂ in air. In the absence of air, crosslinking occurs. Ethylbenzoate forms COOH by Norrish Type II in air and vac.	77
PP (Giegler-Matta Type) (Aash Chem.)	Vac. 30°C	LP 10W Hg Lamp 250m (Tooshiba UV25 filter)		Lumpo's IR Shimadzu RI-27 IR	Degree of swelling decrease	Ash residue (710 ₂) gel fraction.	Degree of swelling decrease with irradiation time in decalin. Gel fraction increase with irradiation time in TCE. These factors indicate crosslinking occurred in vac. PP is resistant to light degradation. The acceleration of photochemical reactions is attributed to the increase in the polymer ash. IR indicates very little change before and after exposure.	78
PP (Isotactic) A 50% crystalline B 80% crystalline	Vac. 200°K to 300°K	DESH-1000 Zenon lamp.		RE-1301 Radio- spectrometer (EPR)		Allyl radical Alkyl radical	(1) The kinetics of transformation from allyl-ethyl to UV and allyl to allyl in the dark at 77-300°K has been characterized. (2) The allyl-allyl transformation is connected with hyper equilibrium excitation of the polymer's crystalline lattice. (3) A theoretical discussion of the photochemical reactions of the polymer in the amorphous and crystalline phases has been confirmed experimentally.	29
PP (Isotactic)	Vac 110°C O ₂ atm. 10-2 torr	DESH-500 lamp 253nm	Phenanthrene	EPR IR UV Spect.		R-O (3200-3400cm ⁻¹) R-O (1670-1720cm ⁻¹)	Heating PP films at 110°C in O ₂ atm. indicated formation of ROO- and R-O radicals. Heating of PP film at 110-130°C for 14 and 170 min. to 110°C caused formation of ROO- and R-O radicals. Photoanalysis of PP with 10 ⁻² wt. % of phenanthrene at 77°K caused methyl radicals to form after 12 hrs. Rate of formation of radicals is proportional to the square of the intensity.	15

Material	Environ. Cond.	Irradiation Source (doses and filter used)	Additive	Anal. Method	Results		Ref.
					Phys. and Optical Effects	Photolysis Products	
PP (Isotactic)	Vac. -196°C 10 ⁻⁵ Torr	(Glass window) used. Total dose filter used: >275nm UV33 >300nm UV31 >325nm UV31 >350nm UV27 >405nm UV25 235-410nm UV-105		ESR		Methyl radicals Free radicals	79
PP (Isotactic)	Vac. 77°K	Philips RPM 12W 253.7-578nm		ESR X-Band 100Mc Field Modulation (Japan Electron Optics Lab. Co.) Model JES-3J		Methyl radicals	80
PP (Isotactic)	Vac. 170°K 260°K 10 ⁻⁶ Torr	Co-60 0.5 Mrad/hr Total dose was 3.5 Mrad.		ESR		Methyl radicals	81

Abbreviations as follows:
PP: Polypropylene
PE: Polycyclic terphenylene

>275nm Small band observed
>300 to >375nm intensity of singlet increased to 2,005.
>227 to no filter showed 4 peaks of methyl radical
>35-410nm also gave methyl radical. When varied at
235-410nm, the singlet intensity increased to 2,005.
Then decayed. This singlet was ascribed to allyl radical
with G (2.005); formed via R-O-O and R-O.

After irradiation spectrum shows diffuse component and
sharp component. Superposition abstraction of the abor-
tion spectrum gives a sharp methyl radical
singlet. Production of free radicals may be due to
impurities.

170°K region corresponds to R-dissociation and 260°K as
to dissociation of PP. Free radicals trapped in polymer
decay with small scale motion of the matrix polymer
(frozen). Less twisted polymer decay with large scale
motion of matrix. Activation energy of decay was
11 kcal/mole at 170°K and 48 kcal/mole at 260°K.

Unsaturated Polymers

Material	Environ. Cond.	Irradiation Source	Additive	Anal. Method	Results		Ref.
					Phys. and Optical Effects	Photochemical Products	
Isoprene-Silver Nitrate Solution	Vac. 10-3 Torr 2 to 15°C	Co-60, 400 Ci/hr 0.7h x 10 ⁶ r/hr Fermox-Ferric Dosimeter		Nitachi TV Spectrometer IR	Insoluble Products	1.2 complex of Isoprene-Al(NO ₃) ₃	42
Polyisoprene (Crepe natural rubber)	Air, r.t.	1000w OSRAM Xenon Discharge quartz lamp 100-600nm 1000m max				<p>330nm max in chain photochemical 555nm = Methylenic bonds, H₂</p> <p>Volatilization residue at 300°C and sulfur acts as protective agent. 700 protects below 370nm, and sensitizes at near visible 160nm deconv. high auto catalytic at the beginning of irradiation. 330nm beginning of photochemical reaction 500nm and higher initial increase in tension noted</p> <p> $k_{\text{is}} = 5.4 \times 10^{-2}$ 330nm $= 3 \times 10^{-2}$ 360nm $= 5.3 \times 10^{-2}$ 350nm </p>	83

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Polyacrylonitrile

Material	Environ. Cond.	Irradiation Source	Additive	Anal. Method	Results			Ref.
					Phys. and Optical Effects	Photolysis Products	Conclusions	
Polyacrylonitrile a). 80-90 wt ethylene carbonate as polymer b). in powder c). as film. glutaronitrile (model cpd.)	Vac. 10 ⁻⁵ torr	(given earlier) 253.7nm (95%)		Beckman DC Spectrophotometer Ball Spectronic 505 Spectrophotometer Oscilloscope Viscometer	Powder form turned brown Film turned yellow in air and dark brown in vacuum. Decrease of η_{sp}	HCN NH ₃ Terminal olefin	Photolysis process in solution was random chain-scission process. The rate depended on history of polymer. Beer-Lambert's law is obeyed in chain-scission acts = 0.04 x 10 ⁴ liter/mole cm. The rate of chain-scission and molecular weight distributions change during reaction which affects viscosity.	46

Polyvinylchloride 1

Material	Exposure Cond.	Irradiation Source	Additive	Anal. Method	Results		Ref.
					Phys. and Optical Effects	Chemical Products	
PVC (Sakum 548)	Vac 10^{-5} mm 80° to 130°	^{60}Co rays, 0.81 rad/sec Pratt dosimeter C/P ratio = 15.6		IR decomposition by volatile with Uicom SP800 SP-7 spectrometer (200-700 cm ⁻¹)	Discoloration red to violet	Polymer Gel fraction	90
PVC (Bazin Q-1812), Gulf Chem. Canada and high am	Air	Rayonet RS 800-200 UV, 3000 Å, 8 W, 1 W simulating sunlight phosphor	TMF (2800 Å max) Dichloroethane (1900 Å max)	Uicom SP800 2000 Å to 7000 Å	Color development 2800 Å - Still in- soluble polymer	Decreased in gelation	91
PVC (Dylen-640) Monsanto	Vac & Air	1 Mrd Van de Graaff generation 1 Mrd/min, total 8 Mev.	Acetylated hydroxytoluene 0.05% (Wt)	Cary 14 Spect ESR	Pent irradiation color top-ation	Polymer	92
PVC	Air 27° to 33°	(glow earler) Potassium ferrioxalate actinometry, 3.6 x 10 ¹⁶ quanta cm ⁻² sec ⁻¹		Microbe combititre for 30		Polymer	93
PVC (Leon 101EF) B.F. Goodrich	Air 40° C	Rayonet chamber, 253.7 nm 3.6 x 10 ¹⁶ e.v./sec/g PVC	Ferrocene (Fc), Copper malicylate Benzene phthalocyanine (CPT)	X-ray fluorescence (Fe) Cary Model 14 Intrinsic viscosity	Gel (CPT)	Gel fraction	94
PVC-PVtBu ether	Air	(given earlier) 1.32 x 10 ¹⁷ /cm (absorption coeff.)		UVC-1 type 1961y film Eluro computer	Gel	Gel fraction isobutyl group intensity	95

Presence of HCl accelerates kinetics and acts as catalyst. Rate dependent on temp & ir. The proportion of crosslinking increases due to irradiation. a) Total unsaturation increases linearly with time. b) Cl abstracts methylene hydrogen to form free radical, thus the formation of double bond.

TMF & C₂H₅Cl enhance uv degra. 253.7 nm degra faster than 300 nm. PVC with residual solvent possess good uv stability. Chain scission is the controlling factor in early stage of degra and crosslinking, the later stage.

Optical density of vac. molded PVC a). Absorption increases. b). Air treated material also increases. c). Concentration of crosslinking increases in all samples. on concentration of crosslinking max same but intensity increase. HMT suppresses conjugated unsaturation. Delocalization produces singlet electron spin resonance.

Rate of dehydrochlorination increases & temp. rate of crosslinking after 1 hr. Rate also depends on intensity of irradiation. After 1 hr the change is controlled by availability of HCl and not a chemical process.

Pure PVC crosslink G_c = 0.29, G_u = 0.30, G_u = 0.06.
PVC Derivatives: G_c = 0.40, G_u = 0.36; G_u = 0.12.
G_u = 0.11, main chain scission G_u = 0.7/100 %.
G_u = 1.0. Crosslinking is enhanced due to chain transfer followed by coupling.

Gel content increases & increase in dose. Gel content increased for crosslinking decreased. Rate of crosslinking is greater than scission. Side group splitting depends on intensity.

Abbreviations as follows:

PVC	Polyvinylchloride
PMMA	Polymethylmethacrylate
PS	Polystyrene
PE	Polyethylene
PP	Polypropylene
PB	Polbutadiene
PA	Polyamide
PAA	Polyacrylic acid
PMAA	Polymethacrylic acid

Polyvinylacetate

Material	Inviron. Cond.	Irradiation Source	Additive	Anal. Method	Phys. and Optical Effects	Photoanalysis Products	Conclusions	M.I.
A PVAc B VC/VPAC (RP) C VC/VPAC (AIBN)	Vac -196 C 35 C 1-5x10 ⁻⁵ torr	Co-60 X source 0.43 Mrad/hr		Varian A60 and T60 IR Price-Phoenix Infrared Photometer Consolidated Electro- dynamic Corp. 21-104	Gelation (2.9 Mrad) Branched polymer AAG gel dose 0.5- 0.7 Mrads	HAc at 100 Mrad PVAc C(x)-0.163	Radiation-induced fracture of approx 1/6th of the branch points in PVAc prior to gel point has been confirmed by m.w. measurement. High sensitivity towards radiation of isolated branched points. 3-4H groups/1000 Vac unit affected by post irradiation. Annealing stabilized photoanalysis. Concentration of trapped radicals decreased with copolymerization, but also with and reactivity differs	101
Abbreviations as follows PVAc: Polyvinylacetate VC: Vinylacetate VPAC: Polyvinylacetate RP: Benzoylperoxide AIBN: Azobisisobutyronitrile								

Polystyrene 1

Material	Environ. Cond.	Irradiation Source	Additive	Anal. Method.	Phys. and Optical Effects	Photochemical Products	Conclusions	Ref.
PS P-MS PMA PMA PVE Pisopex	Vac. 5 Torr 10°C. then heated to 120°C	Nanoval 934-1 153.1 pressure 5x10 ¹⁸ quanta/g/min. Ferrioxalate actinometer 5.8x10 ¹⁸ ergs/g 5.4x10 ¹⁹ ergs/g		Consolidated Electrochemical Dynamics Corp. Model 4000 UV Bendis Time-of-flight Mass. Spect. PE Spectrator Model 4000 uv, Viscometry	Insoluble Relation	4.1×10^4 UV-Vac 1.1 1.4 0.15 0.96 0.94 0.12 2.4 See text for UV-O ₂	PS: Var-uv Crosslinks. Air-uv scission plus crosslink P ₁ most stable compared to others shown and more stable than the P ₂ and P ₃ which are stable in air. P ₁ and P ₂ are stable in air and same order of stability; P ₃ due to resonance stability and ter-radical formed.	32
P-MS-5 0117.1 (Dow Chemical)	Vac. 10 ⁻⁵ 27°C. 115°C. (In the dark)	GEUA-3 Med. Press 280.4, 275.3, 265.4 and 253.7nm		PE-Spectrator Model 4000 UV Consolidated Electro Dynamics Model 21-1031 Mass Spec., Ibbelohde Type Viscometer	Long exposure yellow color	4.1×10^4 0.017 0.016 0.008 0.0028 Ethylene 0.0024 Isobutene 0.0012 Acetylene 0.0012 Benzene 0.0008 Propene 0.0008 Butanes 0.0004 Branched Pentanes	In Vac UV at 27 to 115°C: Chain Scission 6.27×10^{-3} 4.115×10^{-3} Monomer formation Initial degradation is a random scission. Zip length was 7 at 27°C and 25 at 115°C.	33

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Polystyrene 2

Material	Environ. Cond.	Irradiation Source	Additive	Anal. Method	Results		Ref.
					Phys. and Optical Effects	Photoysis Product	
PS/P-MeS (50%) PS/P-MeS (50%) (Dow Chemical)	UV 25 to 40°C	4000 J-Source. 2.35x10 ¹⁰ ev/l-hr G1013 or 2.27x10 ¹⁰ ev/l-hr Ferroous sulfate dosimeter		Statin-type osmo- meter Brice-Phoenix Infrared Spectrophotometer at 40 to 135°C Ubbelohde visco- meter Turbidimetry	Gelation		102
PS. High & Low Density Polystyrene Polyvinylidene chloride	Air 25 to 100°C	Atlas Fadeometer K.38 Fugitometer both carbon arc type Heat treatment	Antioxidant carbon black	Mounsfield Tensio- meter (0.25 in/min.) Charpy impact test Akro impact test Impact test Cambridge textile extensometer (grip/ in/min.) Charpy impact machine Izod impact test at 70° & 100°C for 12 months.	Brittleness, loss of elongation, impact strength and tensile strength.		101

(Values for chain scissions (S) and crosslinking (X) were determined for fractionated and unfractionated polymers having 75-25 and 50-50 mole % styrene.)

75-25: S = 0.11, X = 0.062
50-50: S = 0.11, X = 0.062

g. values = 0.79 and 0.72. Lack of preferential energy transfer is due to the -74 effect to the phenyl group.

Unplasticized toughened PS has poor UV resistance at both natural and accelerated conditions. Pigment improves resistance, black and white providing best protection for U.V. HD polystyrene resists temperature up to 70°C with increase in impact strength with antioxidant stabilizer at 100°C. HD polystyrene is completely protected by antioxidant to natural U.V. but is completely protected by carbon black.

Abbreviations as follows

PS- Polystyrene
P-MeS- Polyvinylmethacrylate
PMA- Polymethacrylic acid
PMMA- Polymethylmethacrylate
PMVK- Polymethylvinylketone
Pisoprk- Polyisopropylketone

Polyvinyl naphthalene

Material	Environ. Cond.	Irradiation Source	Additive	Anal. Method	Results		Ref.
					Phys. and Other Effects	Photoysis Products	
PS (BDH) 1-vinyl naphthalene poly(1-vinyl naphthalene) Copolymer	Air, 77°K	90W Hg Zn Arc broad band center 265nm	Naphthalene	Gary 14 Spect. 50 ft phosphoroscope Rauha & Smith 549 Oscilloscope		Phosphorescence	104
Poly 1-vinyl naphthalene (FVN) P-2-VN FVN/PMMA FVN/PS 1-ethyl naphthalene (1EN) (Model Cpd.)	Air, 77°K	(given earlier) 290nm		Asheco-Bowman Spectrophosphorimeter		Phosphorescence Fluorescence Naphthalenic carbonyl	105
PS PV Naphthalene PMMA							

Abbreviations as follows:

PS: Polystyrene
P-1-VN: Poly 1-vinyl naphthalene
FVN: Polyvinyl naphthalene
P-2-VN: Poly 2-vinyl naphthalene

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Results

Material	Environ. Cond.	Irradiation Source	Additive	Anal. Method	Phys. and Optical Effects	Photolysis Products	Conclusions
PMMA-1 (Kallidoc)	Vac. 10^{-6} torr	Co-60, 81 Raywall 2.5x10 ¹⁷ r/g 2.5x10 ¹⁷ r/g 2.5x10 ¹⁷ r/g	5% Benzoinone 18.6% -di- phenyl ethylene Gravyl (DPM)	Mass Spect Solubility test Viscometry Radioactive Assay	Insoluble material discolor at 4-8 pile units respectively PMMA-1 did not discolor PMMA-2 became yellow on exposure PMMA-3 (Kallidoc) be- came light yellow after 2 units PAN changed from pale yellow to deep amber	PMMA-1, 4 -0% 25°C PMMA-2 Bzn Methylal MeFormate 12.3 Me ₂ O 2.3 CO ₂ 15.7 21.0 MeOH 1.7 0.4 CH ₂ O 3.0 - H ₂ O 30.5 41.1 H ₂ 2.5 CH ₄ 13.1 15.6 H ₂ 11.7 9.5 PMMA-2, 4 CO ₂ Bzn MeAc MeFormate Me ₂ O CO ₂ MeOH CH ₂ O CH ₄ H ₂ CO CO ₂ H ₂ HCOOHe-major no monomer.	Mass Spect. evaluation of PMMA-1 heated at 100°C and at 25°C, the δ of product indicate that at 100°C diffusion of photo-degraded product took place, and its product was not due to free radicals. PMMA-1 heated at 100°C no monomer evolved, the above group rational also apply to PMMA-1. Incorporation of benzoinone or DPPH did not affect the nature of products although some reduction was noted. Little reliance was placed on the results of the mass spect. evaluation. PMMA-2 and PMMA-3 were insoluble. Phenone or DPPH gave 3% soln. in n-pentane. Others were insoluble. Protection was not proportional to the concn. of additive
PMMA (purified)	Vac. and air, 25°C	7 MD Hg Lamp 10 ¹⁷ r/g 10 ¹⁷ r/g 10 ¹⁷ r/g		Bottle Time-of- Flight Mass. Spect Viscometry	Decrease in viscosity no gelation		The quantum action, ϕ , was found to be 3.2×10^{-2} at λ and 1.4x10 ⁻² in air. It is significant that an apparent induction period seems to occur during degradation in air. PMMA in air, however, does not appear to be involved in the formation of new chromophores during degradation.

	Material	Environ Cond.	Irradiation Source	Additive	Anal. Method	Phys. and Optical Effects	Photoysis Products	Results	Conclusions	Ref
6894-139		Air r.t.	Hanovia BR A45 Low pressure. 253.7nm.Ferristal-lace actinometer	O ₂ Aromatic Ben, Phenol, m-xylene Dienes, 1,3-butadiene Cyclohexadiene Ketones- Benzophenone, Biacetyl Nitro Cpd's- Nitromethane 4,4'-d-trinitro- benzoic acid (TNBA)	Viscometry Consolidated Model 21- 620, Mass Spect PE Spectracord Model 4000	(Viscosity decreases End CH ₄ H ₂ CO CO ₂ CH ₃ COOH 0.1% MeOH 0.4% C-Hier. % 0.20	- - - - - -	Two solvents were used in this study CH ₂ Cl ₂ and dioxane. O ₂ Reduced photolysis rate to some extent in both solvents. Transfer of TNBA triplet absorbed energy to the ground state. O ₂ triplet energy could be the deactn. rate reducing without involving peroxide. Aromatics. Energy transfer from benzene triplet to TNBA was estimated as effective rate constant of 2 x 10 ¹⁰ l/mole-sec. Dimerization of nitrobenzene was an effective inhibitor in air or deoxygenated solution. Benzoinone is an exception to the postulate that the increasing in- hibitory effectiveness parallels the decreasing triplet level of the ketone. Competing reactions are involved in the reduction of the rate of degradation of degradation Secondary reactions takes place with biacetyl. Nitro-Cpd. Presence of O ₂ completely nullified the inhibiting effect of nitromethane and TNBA. Nitromethane and TNBA were completely ineffective in dioxane. Rate of formation of charge-transfer complex between the active part of TNBA may be the carbonyl group then the Nitro group. Polymers undergo random scission without extensive de- polymerization. Rate of degradation in air is lower than in vacuo. Primary products are mainly low molecular weight C-C bonds. a. Major reaction is the random homolysis of main chain C-C bonds. b. Minor reaction is the disproportionation to give COOCN ₃ radicals and terminal olefins.	108	
6894		Vac. and air 25°C, 2-mm Hg	GE UA-3 MP uv Lamp (Polychromatic) Actinometry		Viscometry		Film at high temp. (150-200°C) COOH, CO ₂ , CH ₄ and H ₂ per main chain break and at G = 1.6 (62 eV per break).		UV At r.t. random main chain fracture occurs. At higher temp. depolymerization occurs. Energy absorbed for main chain fracture is about 550 eV. In UV which does not propagate > 3 Ray. At r.t. fracture same as in UV. Temperature of chain scission and monomer evolution occur. In both cases the number of fractures were proportional to dose and radicals formed are identical in character. No special contribution was made by any ionic or highly excited species. Thin film with thickness 10 microns. The average energy per bond rupture is 0.9 x 10 ⁻²⁴ eV. 0.18 x 10 ⁻²⁴ eV per bond energy absorbed per break. E=540eV. With Bisolol, E=510eV. Thick film with TV the number of breaks induced per unit dose P ₁ = 8.10 x 10 ⁻² and E = 78.0eV. P ₂ = 1.0 x 10 ⁻² and E = 78.0eV. The precise significance of UV absorption spectrum has not been elucidated.	6

Results

Material	Environment	Irradiation Source	Additive	Anal. Method	Photo and Optical Effects	Photolysis Products	Ref.
PMMA Thickens C 100 C 100 C 100 C 100	Air, P	Neveo J.M. F LP 4g Lamps (Coring H863) 1000 W 1000 W 1000 W 1000 W		Carv Model 11 Spectrophotometer Canon-fenske Viscometer	Viscosity de- creases, yellow- ing, and darkening irradiation		109
PMMA	Air, P	Var de Graaf Generator- 2MeV, 0.5 Mrad/hr Blue Cellophane Dosi- meter Nucleonix Dialyte Actinometer 6 x 10 ¹⁰ W/cm ²	Pyrene, p-t-phenyl Xylene Benzene PB Al	Beckman DU spectro- photometer Canon-fenske visco- meter	Discoloration at 1.5 x 10 ¹⁰ Mrad	Quantum yield, ϕ , of random scission was found to be 2 x 10 ⁻³ . Theory of experimental dose-effect was correlated with first-order viscosity-good fit except for D in benzene solution. A absorption of 553 nm was 37% initial and 14% after 10 ¹⁰ Mrad. The decrease in viscosity with dose exposure decrease to 5.5% efficiency with increasing exposure. The 500m peak was not associated with ketonic or aldehydic carbonyl group in A and B film.	110
PMMA Propionic acid Tricresylphosphate	Vac	LP 4g, 400, 5x10 ¹⁰ E 1- in X-ray constant Potential 5000 Tube Electrodeless Resistometer	H ₂ O ₂	S-Tube capillary Viscometer	UV irradiation 254 nm X-ray irradiation 1.5 x 10 ¹⁰ Mrad CO ₂ 1.5 x 10 ¹⁰ Mrad Isobutene 1.5 x 10 ¹⁰ Mrad	UV irradiation lucite at 253 nm. Pyrene projects peaks as a light filter. La- ser irradiation of lucite at 632.8 nm. Pyrene projects peaks and then back to the chain for excitation. Electron irradiation ϕ = 9 x 10 ⁻³ for main chain scission. The ϕ value is 1.5% Pyrene showed little discoloration per dose. Positive charge transferred to the additive whereby lucite is a scintillator with low ionization potential, such as a negative ion which would be stable after loss of an electron. Presence of air decreases the degradation. Degradation in absence of air is known to be due to the presence of oxygen. The polymers and when these are removed by heating degradation. This was found not to be true. Presence of H ₂ O ₂ in higher concentration enhances degradation. In α -irradiation, in UV irradiation, and in x-ray irradiation, the scission of the chemical group. The H radical from H ₂ O ₂ abstracts hy- drogen from CH ₃ group.	111
PMMA Acetic acid p-tert-butyl p-tert-butyl p-tert-butyl	Vac 1700	Electron beam 250 kV		Merck-Polar-Usometer		Photolysis and thermolysis are compared. In photolysis there was no direct evidence of crosslinking as in thermolysis. Rate of chain scission not dependent on monomer concentration. The rate of chain scission was retarded by increasing the content of degradation process is blocked. In all these aspects photo-reaction is identical with thermal reaction. The main difference found were 1. In photolysis, the rate of chain scission was greater than thermolysis. 2. The rate of chain scission was greater than thermolysis. 3. Monomer liberation in photolysis (1.10) is smaller than thermolysis (1.4).	112

	Material	Environ Cond.	Irradiation Source	Additive	Anal. Methods	Phys. and Optical Effects	Photolysis Products	Conclusions	Ref.
(PMA) (PDMA) (PMMA) (PIA) (PEA) (PiDA) (PiDPA)	Air, r.t.	Toshiba GL-15 LP Hg Lamp			Mitsubishi Perkinas Model 115 Gammameter Japan Spectroscopy Co. Spectrophotometer IR GPC	Yellowing (due to double bonds)	Gel fraction <u>Metacrylates:</u> O ₂ <u>Monomer:</u> <u>Acrylates:</u> O ₂ Acid	Reduction of weight by volatilization increases linearly with increasing irradiation time Volatilization increases with increasing side chain length, except for PMMA. Gel fraction of PMA becomes constant with exposure time (60 hrs) while that of PDMA continues to increase. No gel fraction noted in other polymers. (PMMA small amount). Crosslinking and degradation occur simultaneously except for PMMA. Increase in side group chain length increases crosslinking	117
Abbreviations as follows:									
	PMA-1	Poly(methylmethacrylate)-1							
	PMA-2	Radioactive poly(methylmethacrylate)-2							
	PMA-1	Poly(methacrylic acid)-1							
	PMA-1	Radioactive poly(methacrylic acid)-2							
	PMA-AC	Polyvinylacetate							
	PMA-S	Poly(methacrylonitrile)							
	PMA-N	Poly(n-butylacrylate)							
	PMDA	Poly(dimethylmethacrylate)							
	PMA	Poly(methylmethacrylate)							
	PMA	Poly(n-butylacrylic acid)							
	PisDA	Poly(isobutylacrylic acid)							
	PIDPA	Poly(2-ethylhexyl acrylic acid)							

Material	Environ. Cond.	Irradiation Source	Additive	Anal. Method	Phys. and Optical Effects	Photochemical Products	Conclusions	Ref.
Polyethylene terephthalate (1) ICI-Melinex S (2) DuPont Mylar L (3) DuPont Mylar	Air 20°C 65%	Atlas C-arc photo-measuring PDA-1 600-WR 600-WR	Unknown stabilizers	Wilks #9ATMRS-5 crystal, Beckman IRB, Infrared TIC, Farband spectro- photometer Cannon-Ubbelohde	Film 3-80% elonga- tion after 300 hr. Gelation not ob- served. Brittle.	-OH Increase in fluore- scent with Xenon	All showed basic pattern of degen. and only on degree of unit irradiation time. Film 3 degraded faster than 1 & 2. Xenon irradiation caused more degradation than UV. The 315 to 350 mμ COOH production is due to photochemical not thermalysis of hydrolysis. Xenon arc causes faster rate of fluorescence appearance	47
PET (2L) DuPont Mylar	Vac and air	Oxram super-pressure Hg lamp (SP 500 W); CS-7-5-4 225-420m CS-7-5-4 300-420m CS-D-34 thermopile 2 2-8 & 33.4 mW/cm ²		Gehr HG spectro- balance mass spec. Hewlett-Packard 5750GC Beckman IRB UV Spectrometer	$d = (x10^6)$ 100-420 Vac Air CO ₂ 1.1 8.7 H ₂ 17.2 18.3 CH		(1) Initial reaction leading to COOH formation inde- pendent of environment, occurs via Norrish Type II photo- elimination. (2) CO formation also independent of environ- ment. (3) CO formation photochemical in nature. (4) CO formation occurs in presence of air via hydroperoxide formation. (5) Hy- droperoxide decomposition mechanism secondary reaction involved in formation of fluorescent product. (6) photo- chemical degradation of fluorescent product. (7) photo- chemically degraded to give additional CO+CO ₂ at shorter λ	49
PET, (14-cyclohexy- l-undecylmethyleneterephtha- late)	Vac. and air	Manovia 564.10 mμ. press. Hg arc 253.7nm (filtered)		Malenco-Brown spectrofluorometer	225-420 Vac Air CO ₂ 3.6 28.3 COOH 13.9 20.3		Blue fluorescence occurred intensifying on increased irradiation. Initial fluorescence product Initial fluorescence product 340nm 435nm Second fluorescent product (120hr) - Fluorescent product reduced under N ₂ . Hydrolysis occurs via reaction with -OH or -COOH radicals in air	50
(1) Poly(cyclohexylmethy- leneterephthalate)-CO ₂ - (2) Copolymer, 3-Oxoma- nanediolate (DMCA) (3) Copolymer 6-oxo- nanediolate (DMCA) Each copolymer later was used as model copolymer	Air	AEI Type ME/D Med. Press arc 313nm, 3 x 10 ⁶ einstein/in.		DMR Varian A60 60 MHz PE model 800 GC	d' in scission (1) 0.04/36 hr/ (2) 0.03/85 hr/ (3) 0.03/77 hr/ (4) 0.03/77 hr/ 6.4x10 ⁻³ Einsteins (4-6) propanoate diols, 1,5-di- carboxy-thio-3- pentanediol, d=0.12		Photochemistry depended on n (-CH ₂ -) from carbonyl group. 1. no Norrish Type II photo reduction (DMCA) 2. yield (DMCA) Type II with higher than normal quantum 3. no Norrish Type I and II occur (DMCA) 4. no 5, 6, 7, etc. will behave qualitatively as DMCA but quantum yield for scission is reduced by 0.01 when ketone is in polymer chain compared to the model copolymer.	114

Material	Inviron (Cond)	Irradiation Source	Additive	Anal Method	Phys. and Optical Effects	Prototype Products	Conclusions	Ref.
PEI film - 1-las 9000 (21)	Vac and air	Carbon Arc Atlas Radiometer type FMA-R (Corex D Globe, 35°C, no humidity control)	No additive	Instron tensile tester Type II-C, 21-65% RH viscometer, acid-base titrimeter, Grand percolator (fluorescence) (Mark I) GLC-Haas Spec	Beistle fragile, slight reduction in yield load, increase in break load and reduction in elongation, no change in gel	Chole action COOH and ester group increase in fluorescence due to -OH formation CO ₂ , CO ₂ , 90% CO	Zenon gives shorter than carbon thus provides more energy CO and COOH production are independent of O ₂ presence. They occur as simple photolytic reaction. CO ₂ production is due to photooxidative mechanism, both light and O ₂ involved in photooxidative mechanism and reaction of CO ₂ and COOH and CO ₂ and fluorescence material; Norrish Type I above	115
Same as above	Vac and air	PMK-3 lamp B 9A10 ⁸ E-cm ⁻² sec ⁻¹ (LPM-11 actinometer)		Varian V4502-10 Spectrometer (DPM rel)	Discoloration	Gel	Parameters of crystallinity of E-1 and D-9 was calculated in relation to IV exposure was density is reached. Crystallinity changes takes place in time, no distribution occurs to its most probable distribution on exposure.	117
isophtalic phenylthalein (ref. polymer) 9,9-bis (α-OH-phenyl) fluorene (CD-9 polycarbonate)	Air	60°C 0.3-0.5 Mrad/hr, thermolysis at 60°, 80°, 100° and 120°C		ESR Varian V4502-10		$\begin{array}{c} \text{O} \quad \text{O} \\ \quad \\ \text{d-C-O-CH-CH}_2\text{-O-C} \\ \quad \\ \text{O} \quad \text{O} \\ \text{-C-} \quad \text{C-} \\ \quad \\ \text{O} \quad \text{O} \end{array}$ unassigned III	Disappearance of free rad in amorphous PET is due to mobility of segment even below Tg for crystalline polymer at above Tg to near m.p. radical site hopping by hydrogen atom transfer is the cause of free radical disappearance. The crystalline polymer contains radical III; III increase on heating (crystalline polymer contains radical I).	118
Same as above	Vac 10-4mm Hg		Mono-2-Eu-hydroquinone, 0.01% 2-OH-4-dodecyl oxobenzophenone, 0.25%	Visual appearance Gardner Glossmeter Gardner auto Color	Discoloration, gloss reduction	III	HPC/PA/MA resin gave best results overall color, gloss retention.	119
(1) Phthalic-neopentyl glycol-maleic HPC (2) isophthalic-neopentyl glycol-maleic HPC (3) isophthalic-neopentyl glycol-maleic butylene diol (4) styrene added to above, 40 (5) styrene 21 - HMA 17- added to above	Air	Atlas Weather-ometer Ermaqua Exposure, Ariz. Kingsport Exposure, Tenn		Visual appearance Gardner Glossmeter Gardner auto Color	Discoloration, gloss reduction			51

Material	Environ. Cond.	Irradiation Source	Additive	Anal. Method	Phys and Optical Effects	Photolysis Products	Conclusions	Ref.
Nylon 6 (varn) scoured (MS) Nylon 6 (varn) scoured & absorber (MS) Nylon 6 (varn) scoured & absorber (MS)	Terr (India)	Carbon arc Fade-meter 65% RH, Daylight	2,2'-dihydroxy-4,4'-diamethoxybenzophenone-0.7%	Oswald u-tube, Beckman DB Spec IR-PE	Tensile loss Decrease in wt	Pyrrole, malonic acid	(1) Random scission of C-H bond (2) Poly chain not affected since IR indicates no structural change despite preparation (3) No appreciable change in tensile strength and % (4) Decomposed by free radical leading to formation of peroxide-decomposed to form pyrrole and on prolonged exposure malonic acid formation. (5) H ₂ O soluble degran product (6) IR absorber decreases degran (7) Scouring reduces photo-degradation	120
Poly 4,4'-bis(p-aminophenyl)-2,2'-bithiazoleisophthalimide (BTP) 1,3-aminobenzimidazole benzene terephthalamide (MTP) DuPont Nomex	Air	Nomexia 900w NF Zenon Arc		Jarrell Ash Fl6 3 Plane Grating 0.75 meter spectrograph Microdensitometer Model 14, spectro- photometer	Tensile loss Discoloration BTA: yellow-brown to dark purple MTP: yellow		BTA: discolored by visible light, 41km %wt damaging radiation lines at 370-500nm Secondary inflection at 4.0-4.70m w/p and Nomex discolored and degraded at 70-840nm-tensile loss: MTP and Nomex discolored and degraded at the same wavelength but the mechanisms may be different	12
Nylon 66 DuPont 330 (varn)	Terr (Flt. da) 21,000 Larley, Air 165°F 55% RH	Nuclear (inside core) Nuclear (outside core) Uva-test Mg lamp, 253 7nm Laser (B ₂), Atlas Fade- ometer 300-400nm	Dyes CI 25:159 (yellow) CI 25 (blue) CI 226 (226) metal Manganese stabilizer, Nupol MS	Isotrom (70°F, 65% RH)	Tensile loss		2 hr laser exposure equivalent to 200 hrs of Fade-ometer, a factor of 100. Other mentioned sources were not very useful as accelerated light source. Suggestions have been made concerning further studies.	121
(1) Polyhexamethylene-terephthalamide (poly 6-1) (2) Polyhexamethylene-terephthalamide (poly 6-2) (3) Polyhexamethylene-terephthalamide (poly 6-3) (4) Polyhexamethylene-terephthalamide (poly 6-4) (5) Polyhexamethylene-terephthalamide (poly 6-5)	Air	450w NF, 7g lamp		JASCO CBM-FA Spectr Irradiator TGA & DTA Vilamtu RTC 22 Vilamtu RTC 22 Vilamtu RTC 22 Vilamtu RTC 22	Brittle at 224nm	Translucanamide 272nm Translucanamide 274nm Translucanamide 276nm Translucanamide 278nm Translucanamide 280nm	Photo-degradable polymer. Poly 6-1 degrades faster than poly 6-5 due to ester effect at 224nm. No effect of aliphatic chain length on de-polymerization rate has been detected. Poly 6-1 gives two types of scission a. Symmetrical-gives rise to non-climeneyl groups-272nm b. Asymmetrical-gives rise to the trans-stilbene and one fumarimide linkage Thermal study revealed polymide stability to 310°C.	122
Nylon 66 (varn 210 filament, 6 den)	Air, 20-160°C	Harlow Zero-Test, 6000w Filtered with Dow Corning filter glass Nos 0-53, 0-54, 0-52, 3-73		Beckman Model DU Spectrometer Cary Model 111V	Discoloration Increase in tensile strength loss	NOOH, (160-170nm) after 120 hr exposure	Photodecomposition by photon attacking the amide linkage abstracting H from carbon 8 to M-2 carbon radical reacts with am. O ₂ to form peroxide. After peroxide formation, the amide linkage is broken during irradiation. Peroxide decomposes at 100°C. Occurrence of other 3 degrees sensitizes photo-degrad	123

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Siloxanes

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Material	Environ. Cond.	Irradiation Source	Additive	Anal. Method	Results			Ref.
					Phys. and Optical Effects	Photolysis Products	Conclusions	
Polydimethylsiloxanes (MMS) DC 50, 41 fluid DC 350, 41 DC 104 Methyl phenylsiloxane (MPS)	Vac. 10^{-5} torr	Xenon resonance lamp, 167nm 3.340, 2×10^{15} photon/sec. Krypton lamp, 133.6 & 116.5nm 3.34, 0.7×10^{15} photons/sec.		Quadrupole Mass spec, McLeod gage, Gas press. Dual pressure oscilloscope recorder Viscometry	Viscosity increase	IMS 167nm Surface Mode H ₂ (0.009) CH ₄ (0.020) C ₂ H ₆ (0.033) Immersion Mode H ₂ (0.021) CH ₄ (0.087) C ₂ H ₆ (Not detected) 123.6nm Surface Mode C ₂ H ₆ CH ₄ H ₂ C ₂ H ₄ C ₂ H ₂ H ₂ Immersion Mode CH ₄ (0.087) H ₂ (0.049) MPS 167nm Surface Mode CH ₄ (0.001) no C ₂ H ₆ H ₂ (0.004) Immersion Mode Same as above	Mechanism illustrated 167nm Surface mode cleavage to form CH ₄ . Immersion Mode and Surface Mode H ₂ formed by abstraction Si-C change is more probable also primarily excited. 123.6nm C-H bonds are primarily excited	61
Methyl siloxane Resin (from methyl-trimethylsilane and cyclo-dimethylsiloxane)	Air	Atlas Weather-o-meter 6000h, Xenon Arc 281nm Hg vapor lamp, G1-GA311-4w (conventional lamp)		PE-337 UV PE-137 IR		Xenon Arc Gives wavelength greater than 281nm and intensity greater than 100 mW/cm ² . Si-CH ₃ bond cleavage due to C-H and Si-C cleavage. Mercury Vapor Lamp (185-435nm, 66-155 kcal/mole) Si-CH ₃ bond cleavage indicated at 3.0 band. Also Si-CH ₃ bond formation showed at 8.85 and 9.5 bands. Mechanism illustrated. Water was not removed from sample which could react to form Si-OH.	MPS indicated no long range energy transfer along the chain	62

Material	Environ. Cond.	Irradiation Source	Additive	Anal. Method	Results			Ref
					Phys. and Optical Effects	Photolysis Products	Conclusions	
Polydimethylsiloxane (PDMS) Polydimethyldiphenylsiloxane (PDMDPS) (7 mole % diphenyl units)	Vac. H_2O Air H_2O/H_2 - 20% 80%, 38°C	$60Co$ 5000c γ flux 2.6×10^5 r/hr		Vibrating Reed Technique	Discoloration XIR - light yellow vac - no change H_2O - orange No change H_2O/H_2 - light yellow PDMDPS XIR - red brown vac - light yellow H_2O - red brown No change H_2O/H_2 - orange	-SiMe ₂ O- -SiMe ₂ O-0.25 -SiMe ₂ O-0.13	Vibrating reed technique (20-100 cps) used to study rate of crosslinking. (1) Crosslinking rate, k_c , of PDMS is dependent upon the irradiation atm employed. ORDER OF RATES, PDMS $k_{vac} > k_{H_2O} > k_{H_2} > k_{air} = k_{H_2O} + k_c$ PDMDPS similar except k_{air} slower than $k_{H_2O} + k_c$ (2) 20% $H_2O/80\% H_2$ yielded identical rates and color at equivalent dose rates. PDMDPS discolored more than PDMS mechanism not known (3) Crosslinking rate apparently controlled by the concn of H_2O and radiolytic by-products of H_2O , $O_2 + NO_2$, $U_2 + NO_2$ - decreases crosslinking. H_2 is same as H_2O in vacuum. (4) PDMDPS crosslinking rate is not significantly influenced by the stability of the end groups i.e. -SiMe ₂ > -SiMe ₂ ϕ > -Si ϕ Me etc. The source of color formation not explained	125
Aryldimethylsiloxane Polydimethylsiloxane	Air, r.t.	GF Resonant Transformer 1.5 Mr/sec Dose rate 20 Mr/min.		Cannon-Ubbelohde Viscometer Ellipsoscope k_{H_2}	Gelation	-SiMe ₂ O- -SiMe ₂ O-0.25 -SiMe ₂ O-0.13	In pregel region crosslink is temp-independent. Parameter, ξ , represents the parallel displacement of the arhenius ($\log \eta$ vs $1/T$) viscosity curve. Therefore, ξ is proportion of aromatic substituents conferring stability than single aromatic. Homopolymer more stable than copolymer in aryl alkyl groupings	64
Dimethylsiloxane Oil G.E.	Vac. H_2 , r.t.	800kv electron source 100Mr/hr. 1.2Mr 1.4Mr 1.6Mr 1.7Mr		Viscometry, light scattering, osmometer	Gelation		Qualitative study of intrinsic viscosity study with irradiation, $(\eta)/(\eta)_0$ not very sensitive to γ unless $1 < \gamma < 10$ Outside this range other methods should be used. Doses 1.2Mr and less were filtered through fine filter. $(\eta)/(\eta)_0 = 2.04$ 1.4Mr would go through coarse filter. 1.6 and above did not go through coarse filter $(\eta)/(\eta)_0 = 2.24$	176

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Poly(Alkylene Sulfides)

Material	Environ. Cond.	Irradiation Source	Adding	Anal. Method	Results			Ref.
					Phys. and Optical Effects	Photoysis Products	Conclusions	
$(CH_2-SS)_n$ (MMS)	Vac. 5 $^{\circ}$ C 10 ⁻⁴ torr	Med. Press. Hg lamp CE (2x10 ¹⁴ quanta/sec-cm ²) 200-400nm range		Consolidated Eng. Co. Model 21-240 mass spec. C1c	wt. loss brittle, cracking, curling, yellow film from polymer- sulfide. Brown film from polycarbon mono- sulfide.	H_2S & PH_3 H_2S } major CS_2 CH_3SH minor CH_3S	wt. loss: PRTS 80% PRTS 511 Degradation under tetrasulfide-sulfide polymer sulfide degraded sample remitted and exposed showed no change in wt. loss. Methylene polysulfides evolved the most H_2S . CS_2 was the major product of the methylene polymer only.	127
$(CH_2-SSSS)_n$ (MMS)								
$(CH_2-CH_2-SS)_n$ (MMS)								
$(CH_2-CH_2-SSSS)_n$ (MMS)								
<p>Abbreviations as follows:</p> <p>MMS: Polymethylene sulfide MMS: Polymethylene tetrasulfide PRTS: Polymethylene tetrasulfide PRTS: Polymethylene tetrasulfide</p>								

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Minerals and Pigments

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Material	Environ. Cond.	Irradiation Source	Additive	Anal. Method	Results		Ref
					Phys. & Optical Effects	Photolysis Products	
1. PS/2-Et-NaCl/AcN 2. VCl/Ac (60% VCl) 3. VAc/Eumbrate (18%) 4. VAc/Ac/Si (15% Ac & 5% Si) 5. VAc/Ac (15%) 6. Ac Pure 7. VAc/dibutylphthalate	Alr 30, 60 & 95% RH, 55°C	Zenon Arc Weatherometer (RH 60%, 55°C) Various filters	ZnO Abc (A from Zn metal waste, B from pure ingot) TiO ₂ (Amdur)	Weight loss	Chalking	H ₂ O ₂ (formation postulated)	132
HDPE LDPE Impact PS Rigid PVC PP	Alr, 55°C	GE RS-4 Sun Lamp 280-380nm 200w Flood lamp	ZnO, secondary additive. 1. Polygard (tri sized-mono and dinonyl phenyl phosphite) 2. DTPP (dilauryl thiopropionate) 3. Tiganox 1076 4. Tiganox P (organic absorber) 5. Ethyl Zimate		Time to failure 1. Flex break 2. Brittleness 3. Heavy pitting 4. Chalking 5. Severe cracking 6. Severe crazing 7. Edge crumble 8. Severe discoloration		133

Abbreviations as follows:
PVC Polyvinylchloride
PS Polystyrene
MS Methylsilicone
VAc/AA Vinylacetate/
acrylic acid
PAC Polyacrylate
PA Polyacrylic acid
MAA Methylmethacrylate
AcN Acrylonitrile
AC Acrylic acid
ABG Abg density
P Polyethylene
P' Polyethylene
P Polypropylene

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